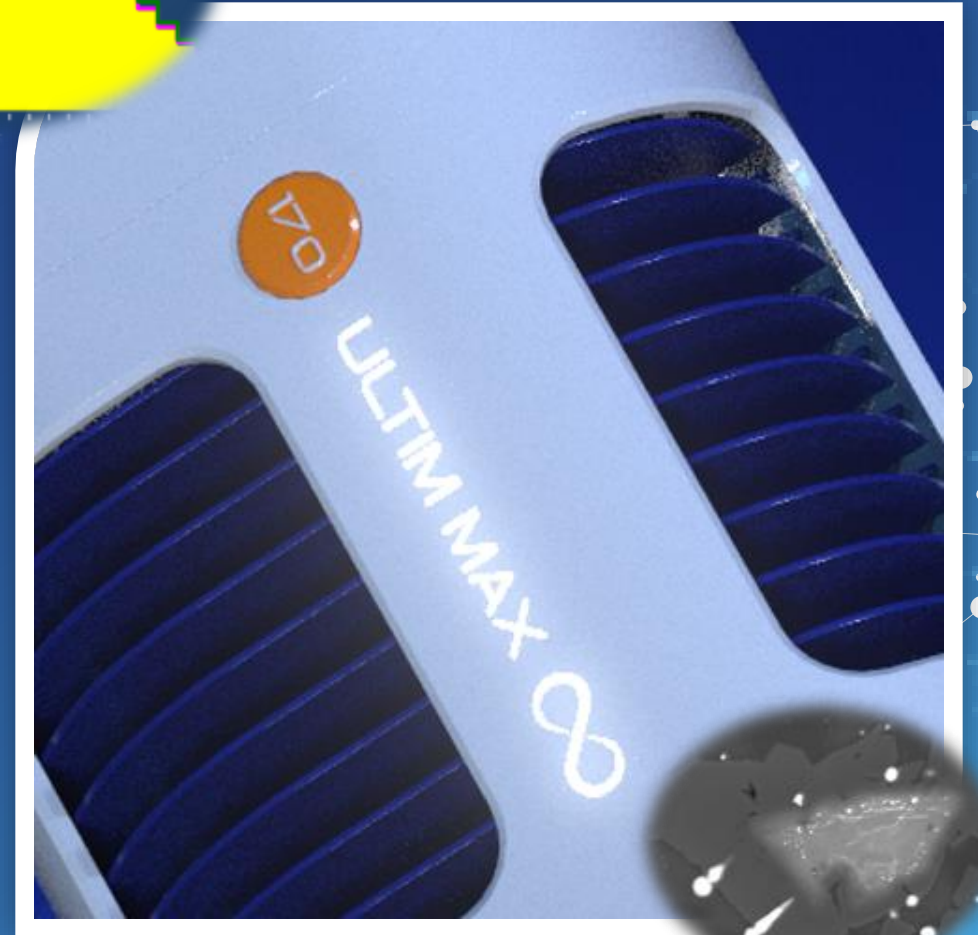
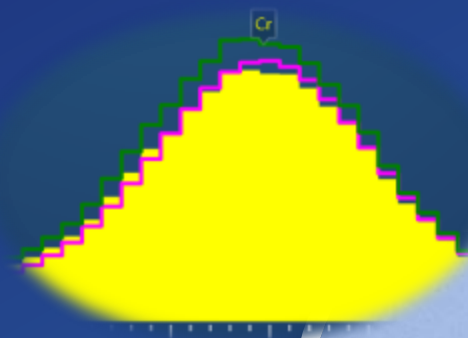


How to bring WDS capability to your SEM using the latest EDS technology?

Dr. Lucia Spasevski

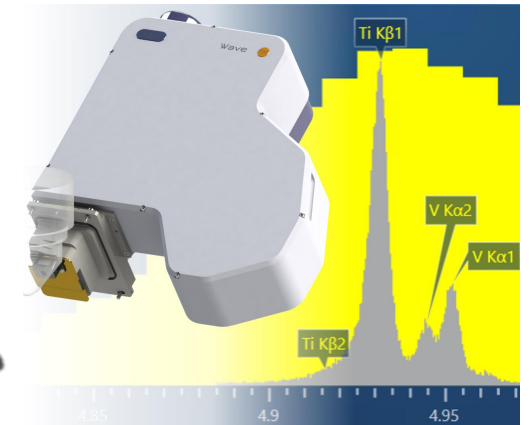
Product Manager

Oxford Instruments Materials Analysis – Electron Microscopy



Overview

- **The growth in capability of EDS detector and data processing** has significantly reduced the advantage of a WDS system on the SEM.
- Applications where SEM-WDS analysis was traditionally the only means of producing reliable data are now increasingly rare
- EDS can more often provide an equivalent result using more familiar workflows and methods
- Modern EDS detectors supported by **Tru-Q IQ spectrum processing (new Ultim Max Infinity detector)** support applications where WDS has traditionally been preferred.
 - **Peak overlaps**
 - **Light element analysis**
 - **Minor and trace element constituents**
 - **Quantitative analysis**
- EDS advantages:
 - **Significant improvements in speed, versatility, and ease-of-use**
 - **Combination** with the first of its kind **BEX** (backscattered electron and X-ray imaging) detector

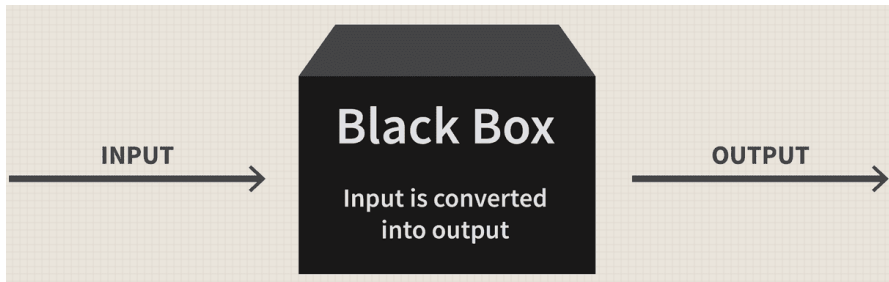
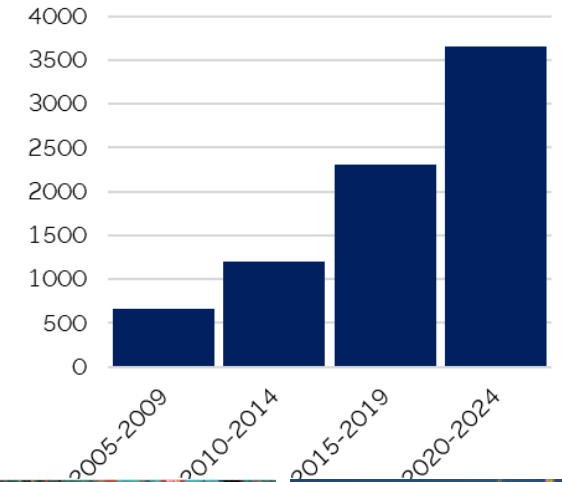


Why EDS is not used more for quant

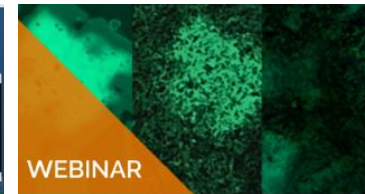
- EPMA started with WDS
- Microprobe are instrument designed for quant, SEM are more general purpose
- Misconception that EDS does not have enough spectral resolution for quant
- Vendors offer one button click quant. Good for users that know what they are doing, bad for users that don't.



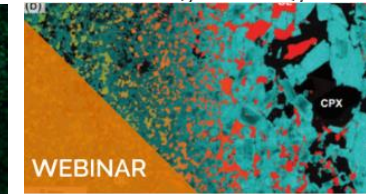
Google Scholar Results:
"comparison of SEM-EDS and
EPMA"



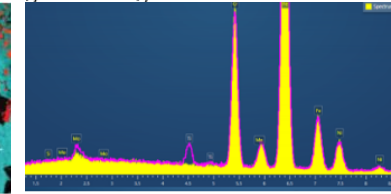
On Demand
Duration: 60 mins
Practical guide to high count rate EDS analysis
This webinar covers high count rate capabilities of EDS systems, consequences of working at high rate and main limitations. We also demonstrate how to perform this type of analysis.
[Read more >](#)



On Demand
Duration: 60 mins
Modern SEM-EDS Systems Explained - What is cutting edge technology today?
Cutting edge SEM-EDS systems can achieve extraordinary results achieving accuracy, speed and sensitivity that may surprise you. This educational session unlocks the key requirements.
[Read more >](#)



Biomaging & Life Science | Batteries & Fuel Cells
On Demand
Duration: 1 Hour
Quantitative EDS Explained: How to achieve great results with or without using your own standards
[Read more >](#)



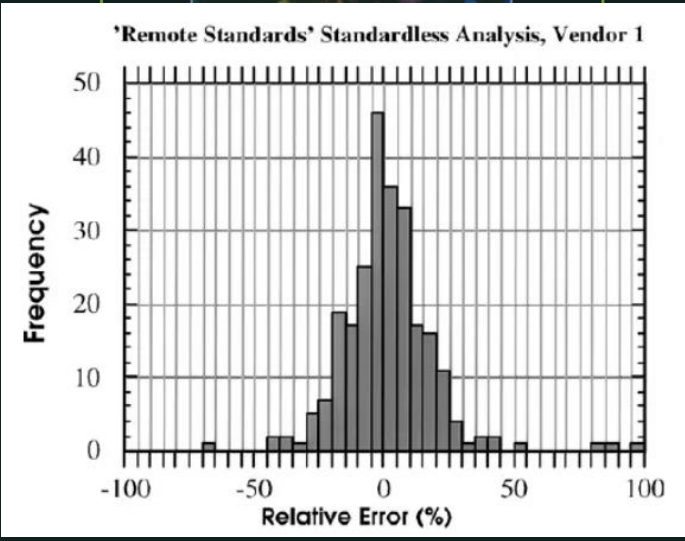
Fri Oct 14, 2022
4 min read
Determining accurate detection limits for EDS analysis using simulated spectra
Simulate accurate EDS spectra for any material, to calculate detection limits and if you can find an element using EDS before you collect any data from a sample.
[Read more >](#)

Rationale- Pushing for Greater EDS Acceptance

What Does the Literature Say?

2003

Scanning Electron Microscopy
and X-Ray Microanalysis



“EDS spectrum processing is a “black box”

“Overlaps are so severe analysis of an element of interest cannot be carried out”

“Very difficult to detect the presence of a minor element”

“Standardless analysis produces “marked loss in accuracy”

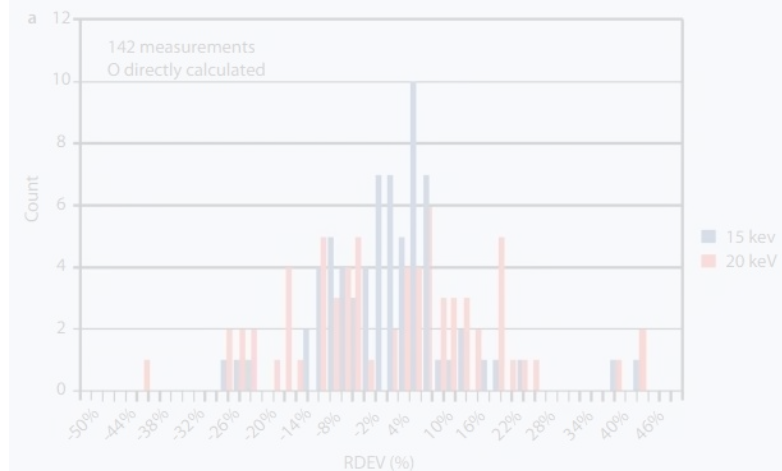
“Standardless always normalised”

2017

Joseph J. Goldstein

“the level of accuracy achieved with this SDD-EDS approach fits within the RDEV histogram of EPMA-WDS for major, minor and trace constituents”...

Scanning Electron



Calibration should be performed regularly

Comparison between EDS and WDS data in journals

- Despite lower P/B ratios and worse spectral resolution, EDS has been shown to achieve high accuracy equivalent to that of WDS even in the cases of minor and trace elements with severe interference from a major element

Newbury DE, Ritchie NW. Performing elemental microanalysis with high accuracy and high precision by scanning electron microscopy/silicon drift detector energy-dispersive X-ray spectrometry (SEM/SDD-EDS). *J Mater Sci.* 2015;50(2):493-518. doi: 10.1007/s10853-014-8685-2

Dale E Newbury, Nicholas W M Ritchie, Measurement of Trace Constituents by Electron-Excited X-Ray Microanalysis with Energy-Dispersive Spectrometry, *Microscopy and Microanalysis*, Volume 22, Issue 3, 1 June 2016, Pages 520–535, <https://doi.org/10.1017/S1431927616000738>

- Newbury and Ritchie studied a glass standard K2496 containing Ba (major concentration of 42.99 wt%) and Ti (minor concentration of 1.8 wt%) and obtained a relative error of 2.4% for Ti; for BaTiO₃ the deconvolution of Ba L and Ti K X-ray peaks is required for the accurate quantification.

The small relative error demonstrates the deconvolution of EDS X-ray peaks is possible even if one of the deconvolved X-ray series has a much lower intensity than the other.

- By acquiring spectra with 120 million counts, they detected the presence of 0.41 wt% Ta (overlapping with 11.5 wt% Si) and 0.41 wt% Ce (overlapping with 21.94 wt% Ba) in the K873 glass standard but obtained a worse quantification accuracy (~25%) than with major and minor element interferences
- The authors operated their EDS detectors with a time constant yielding a Mn K α resolution of 128.5 eV and a dead time of ~10%, resulting in a low output count rate and long measurement time

What were the most common applications of SEM-WDS?

Setting the goal for EDS data quality

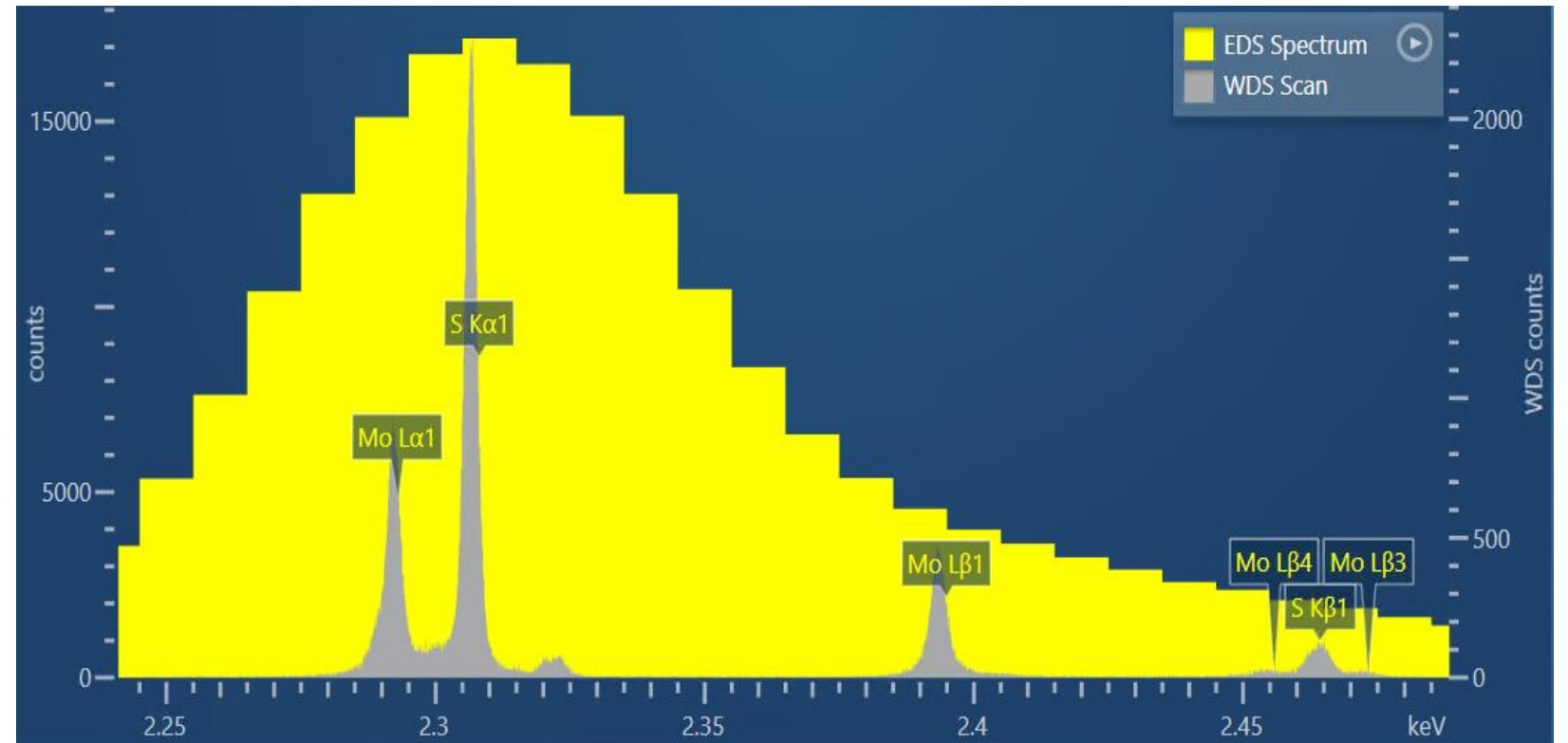
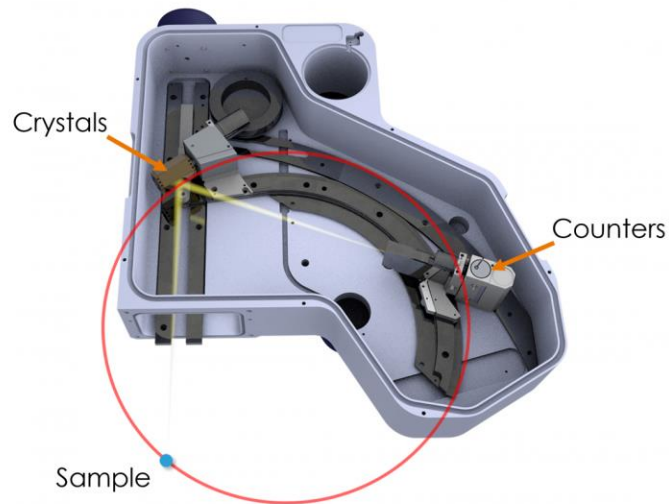


SEM-WDS Applications: Peak Overlaps

Wave had the highest spectral resolution achievable on an SEM

- Diffracts select X-ray energies using Rowland circle geometry
- Bent and ground crystals and a motorised counter entrance slit further optimised resolution for every X-ray line
- Si $K\alpha$ = <2 eV
- Fe $K\alpha$ = <25 eV

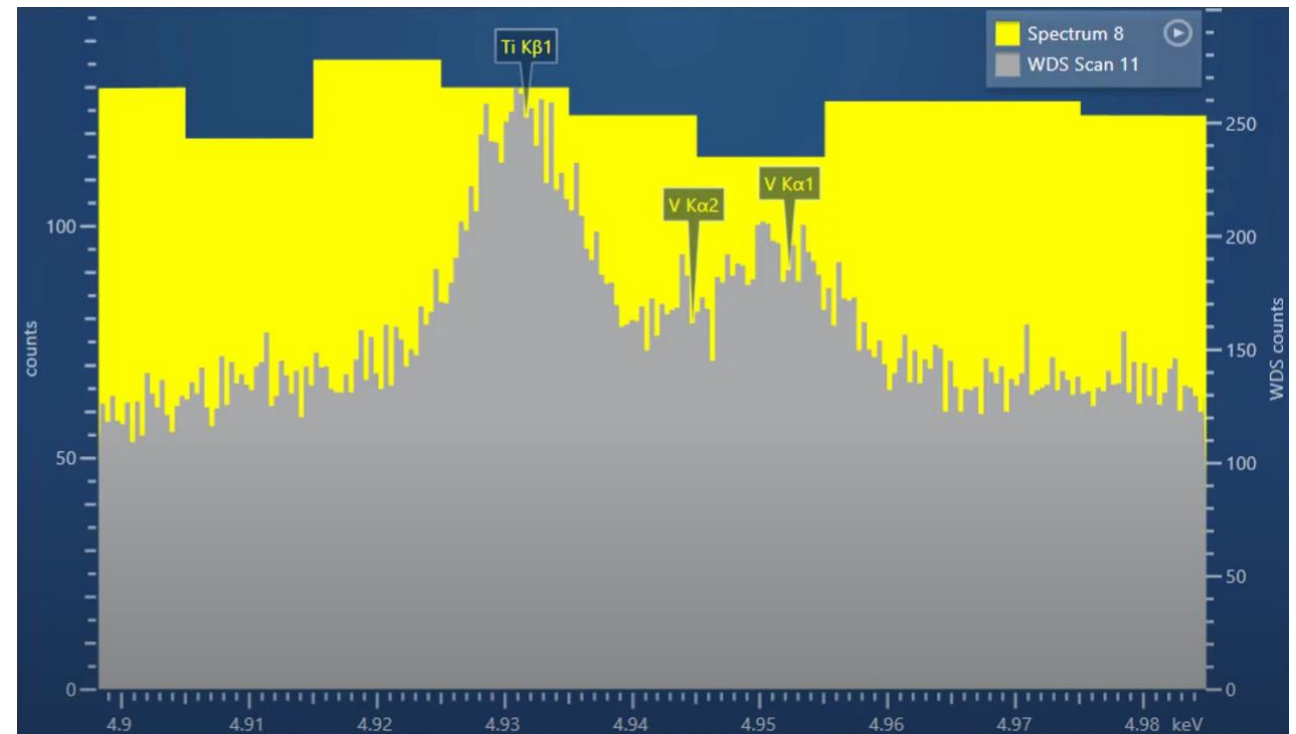
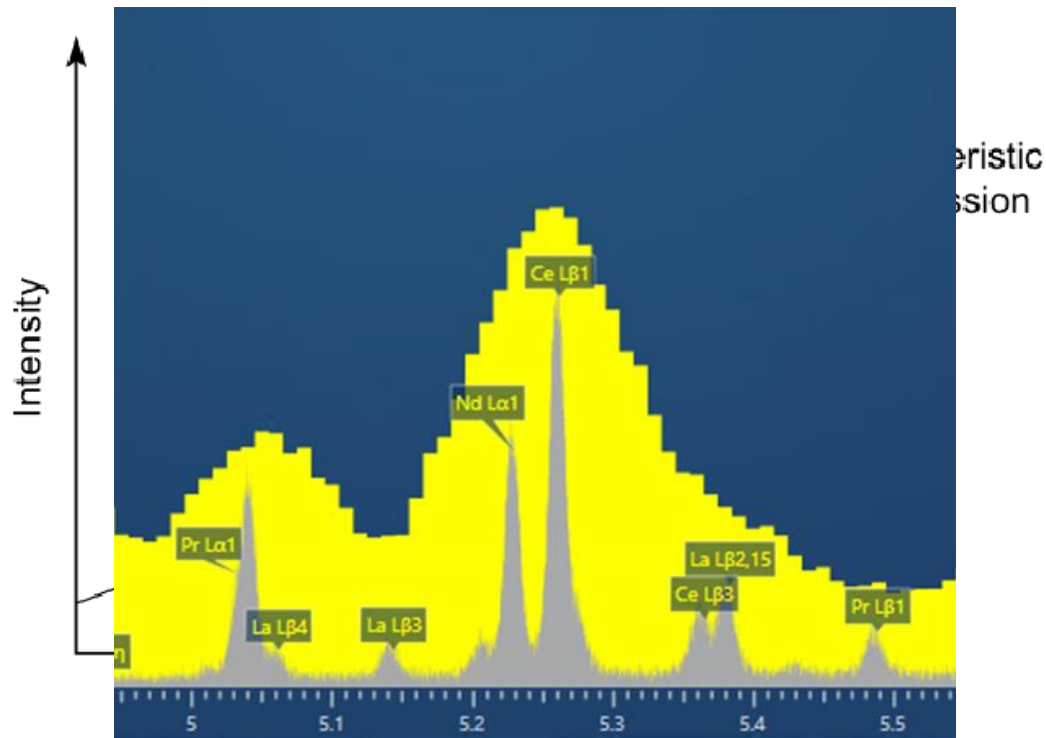
Problematic overlaps:
Mo/S, Ba/Ti, Ti/V, Cr/Mn,
Fe/Co, REE, PGM, Re/W/Hf



SEM-WDS Applications: Minor and Trace Elements

WDS is a powerful and well accepted technique quantification at several wt.% - 10's ppm

- High peak to background signal- EDS is impacted more by Bremsstrahlung
- Detection limits frequently less than 100 ppm, Si = 9 ppm, Fe = 15 ppm
- Spectral resolution is important where traces are similar eV to major elements



SEM-WDS Applications: Quantitative Analysis

WDS is a longstanding and well accepted method for quantitative analysis:

- High accuracy- totals 100 ± 2 wt.%, $\sigma < 2\%$
- Standardisation is imperative and performed regularly
- Improved counting statistics on minor-trace elements

Quant Results View

Active	Label	N	Mg	Ga	Total
●	WDS Point 1 sample A 10kV...	17.1975	0.0605	81.4222	98.6802
	WDS Point 2 sample A 10kV...	17.0411	0.0642	82.2987	99.4041
	WDS Point 3 sample A 10kV...	17.0472	0.0696	82.4043	99.5212
	WDS Point 4 sample A 10kV...	17.0805	0.0642	82.1395	99.2842
	WDS Point 5 sample A 10kV...	17.2017	0.0670	82.1684	99.4371
	WDS Point 6 sample A 10kV...	17.1978	0.0674	82.0898	99.3550
	WDS Point 7 sample A 10kV...	17.1634	0.0649	82.4333	99.6616
	WDS Point 8 sample A 10kV...	17.1977	0.0631	82.2233	99.4841
	WDS Point 9 sample A 10kV...	17.1187	0.0670	82.4766	99.6623

Statistics

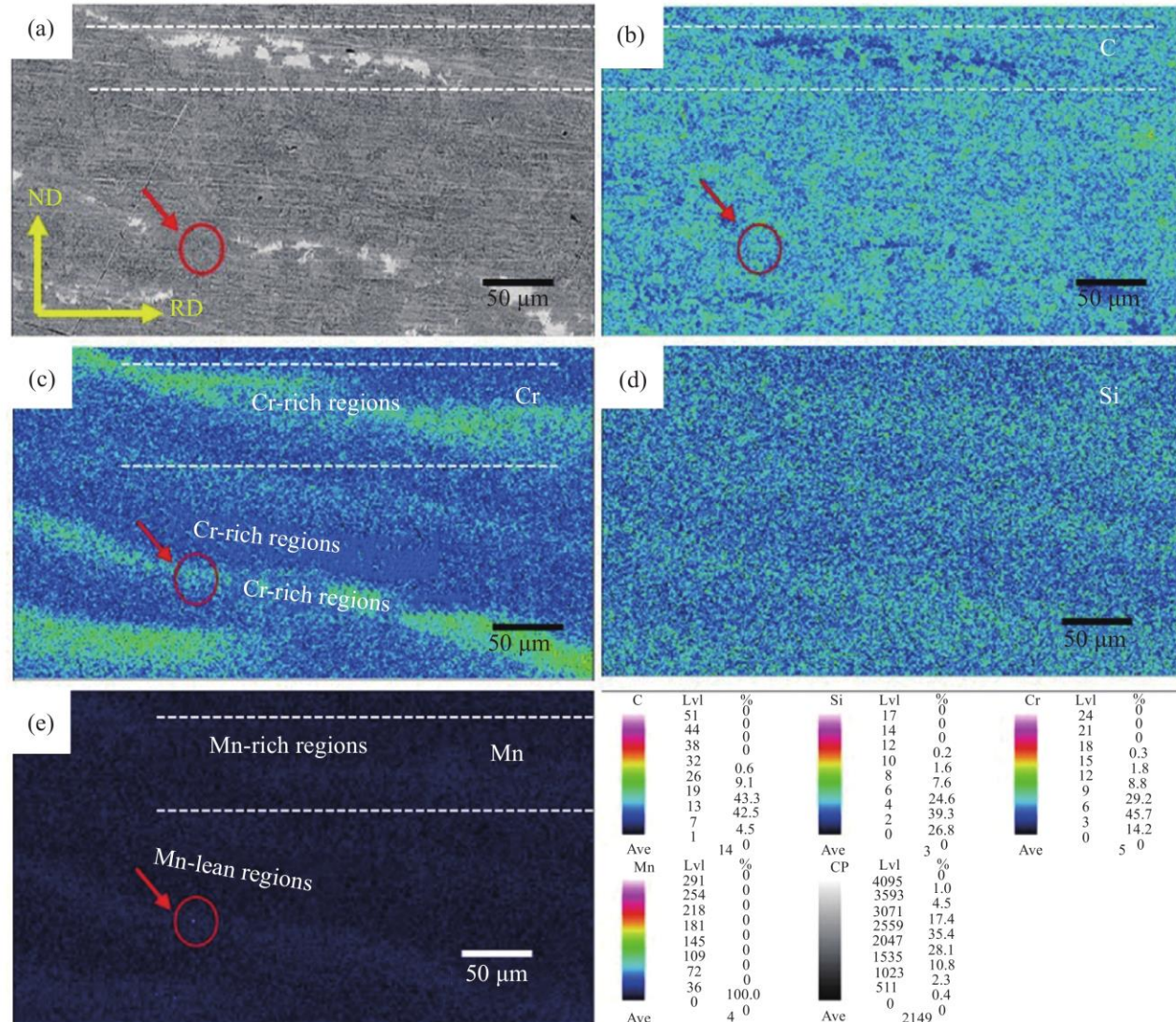
Statistic	N	Mg	Ga
Max	17.2017	0.0696	82.4766
Min	17.0411	0.0605	81.4222
Average	17.1384	0.0653	82.1840
Standard Deviation	0.0677	0.0027	0.3167

Olivine analysis		Element wt.%								
		Si	Fe	Ni	Mn	Mg	Ca	O	Total	
EPMA	Electron microprobe	Average	16.87	25.90	0.03	0.42	18.25	0.02	38.79	100.28
		1σ	0.085	0.396	0.011	0.021	0.211	0.008	0.172	0.474
AZtecWave	SEM WDS-only	Average	16.79	25.39	0.04	0.43	18.56	0.01	38.75	99.97
		1σ	0.327	0.309	0.014	0.027	0.310	0.004	0.268	0.487
AZtecWave	SEM EDS+WDS	Average	17.02	25.24	0.04	0.43	18.14	0.01	38.69	99.57
		1σ	0.059	0.320	0.014	0.027	0.204	0.004	0.118	0.201

SEM-WDS Applications: Mapping

WDS was used to perform 2D mapping of minor and trace element constituents:

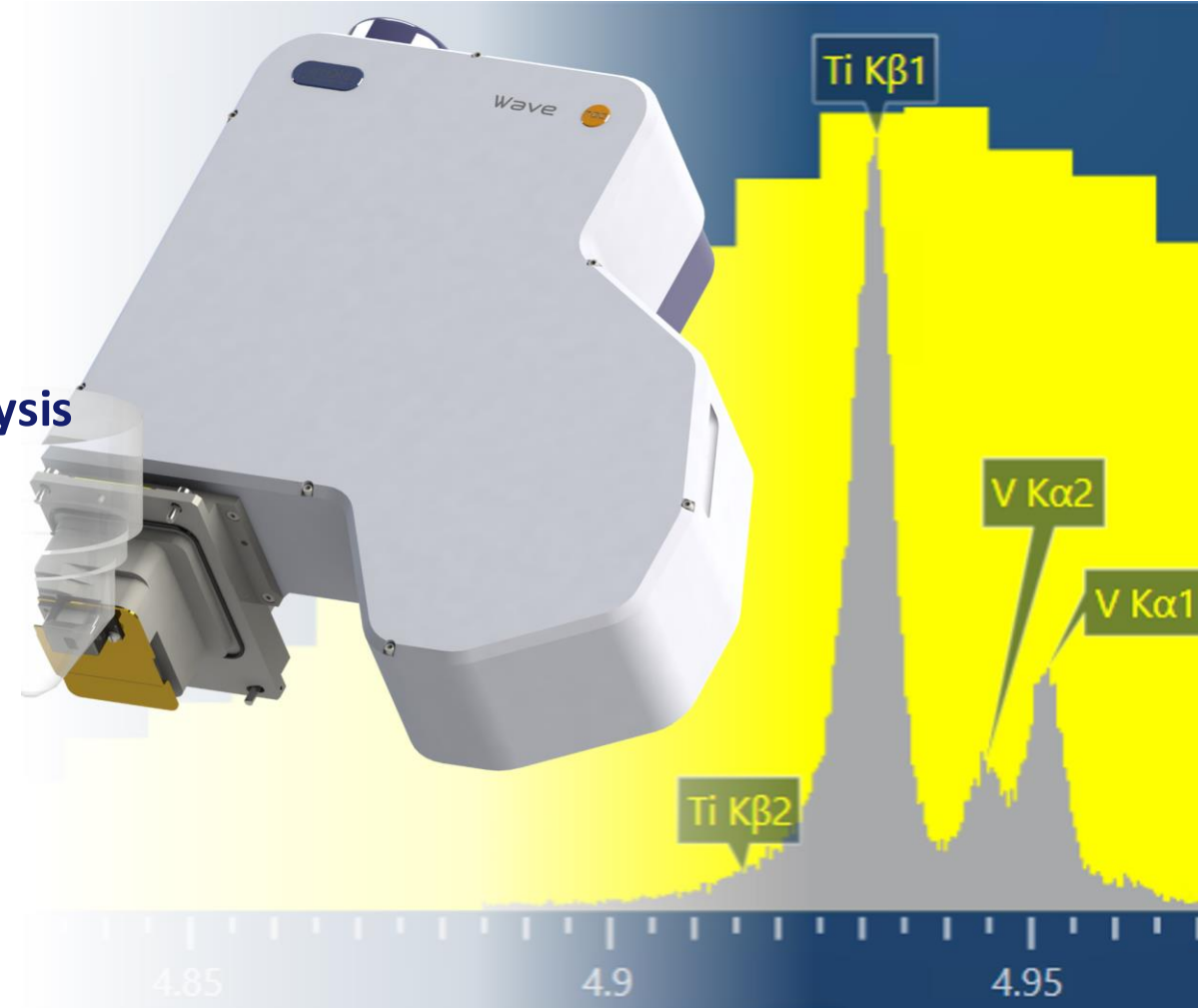
- Minor-trace element mapping
- High precision resolves subtle variation
- Eg diffusion in steel/variation in minerals
- High speed EDS produces spectral artefacts



Summary SEM-WDS Applications

WDS major application areas

- Analysis of difficult spectral overlaps
- Characterisation of minor and trace elements
- High precision and high accuracy quantitative analysis
- Minor-trace element mapping



How EDS Caught up with WDS

Technological advances in SEM-EDS



Leaps in EDS Technology: Digital Spectrum Processing (1995)

Early EDS systems relied on analogue electronics for signal processing, but digital electronics quickly became the dominant technology.

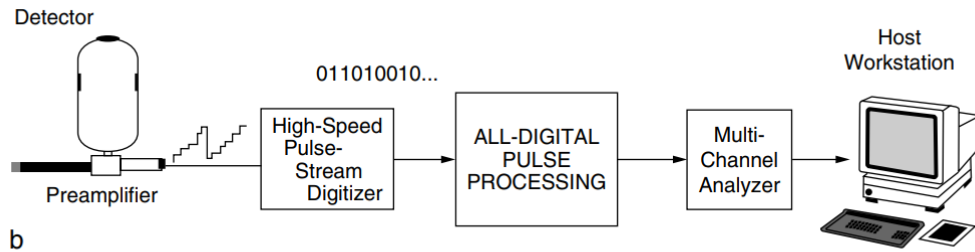
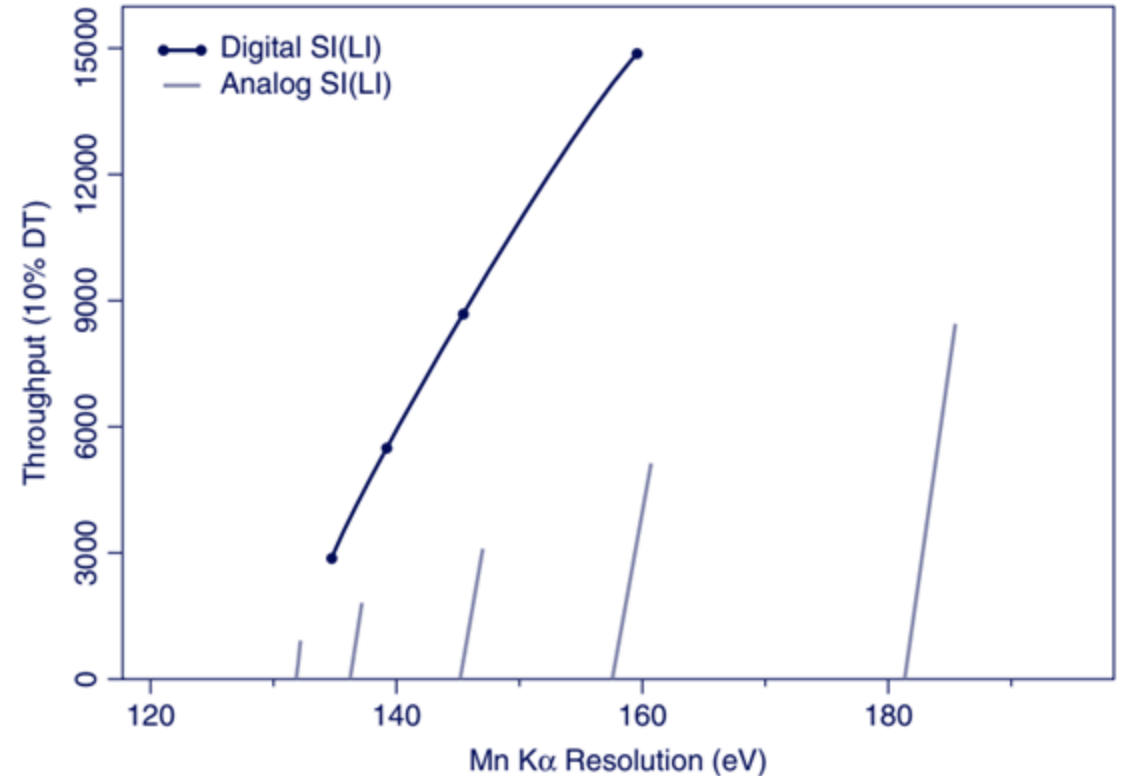


Figure 7.12. Comparison of digital and analog pulse processing. (From Mott and Friel, 1995; courtesy of Princeton Gamma Tech.)

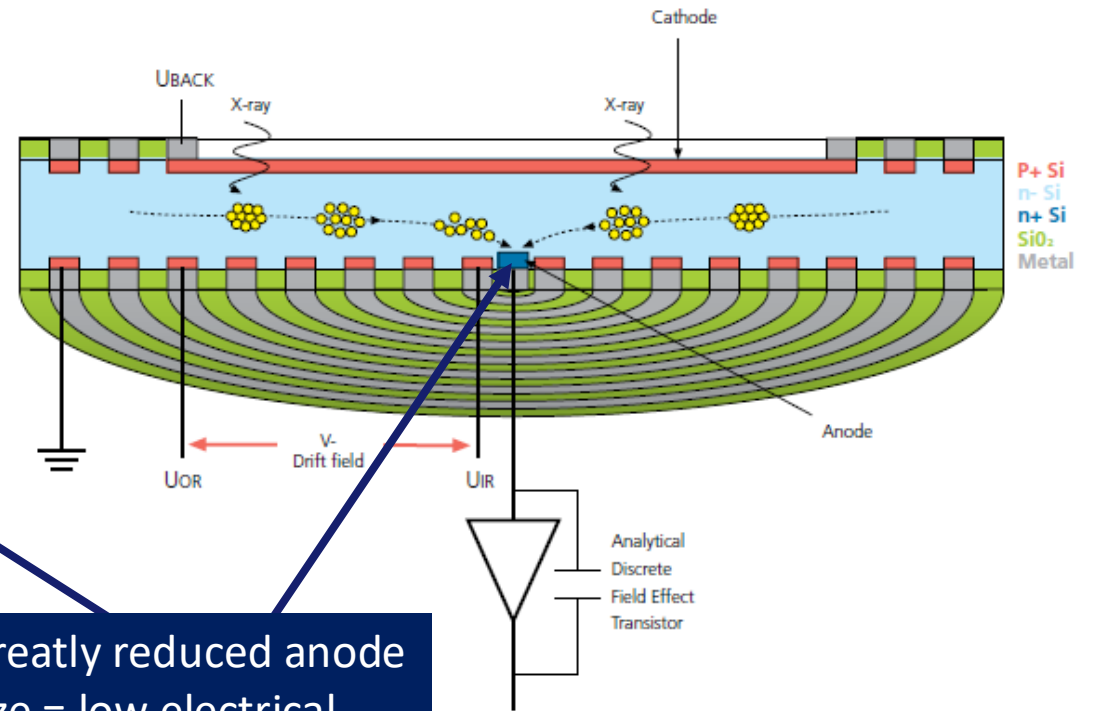
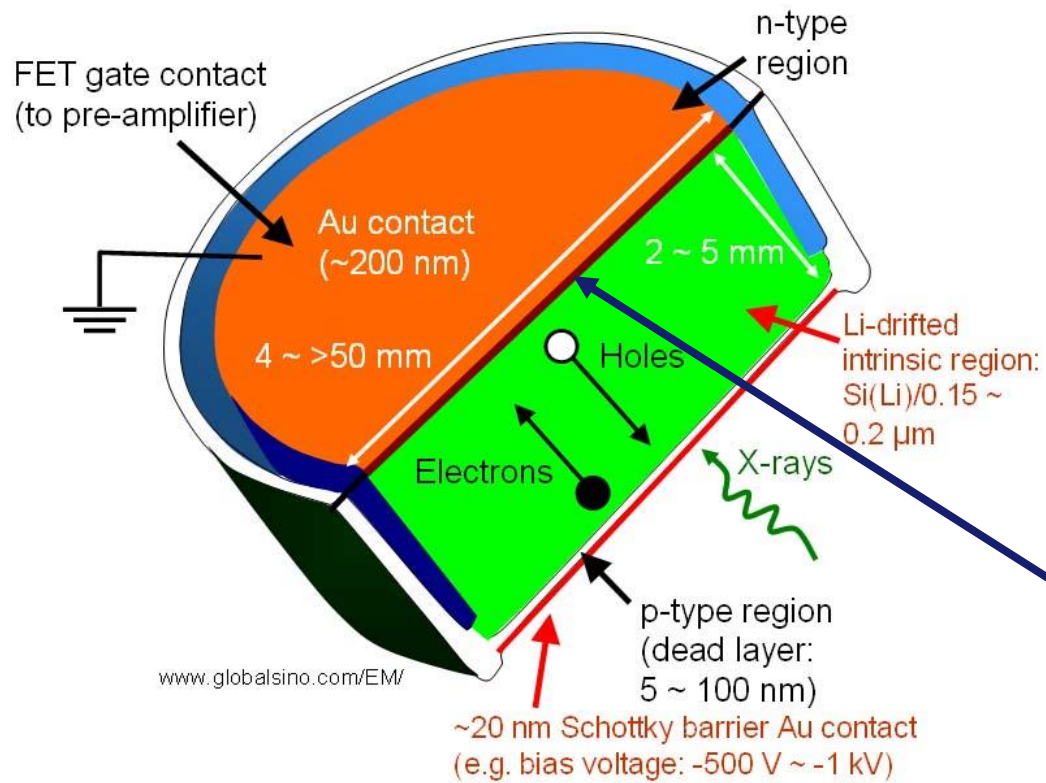
- Speed
- Resolution
- **Day-to-day stability**



Leaps in EDS Technology: Transition from SiLi to SDD (2000's)

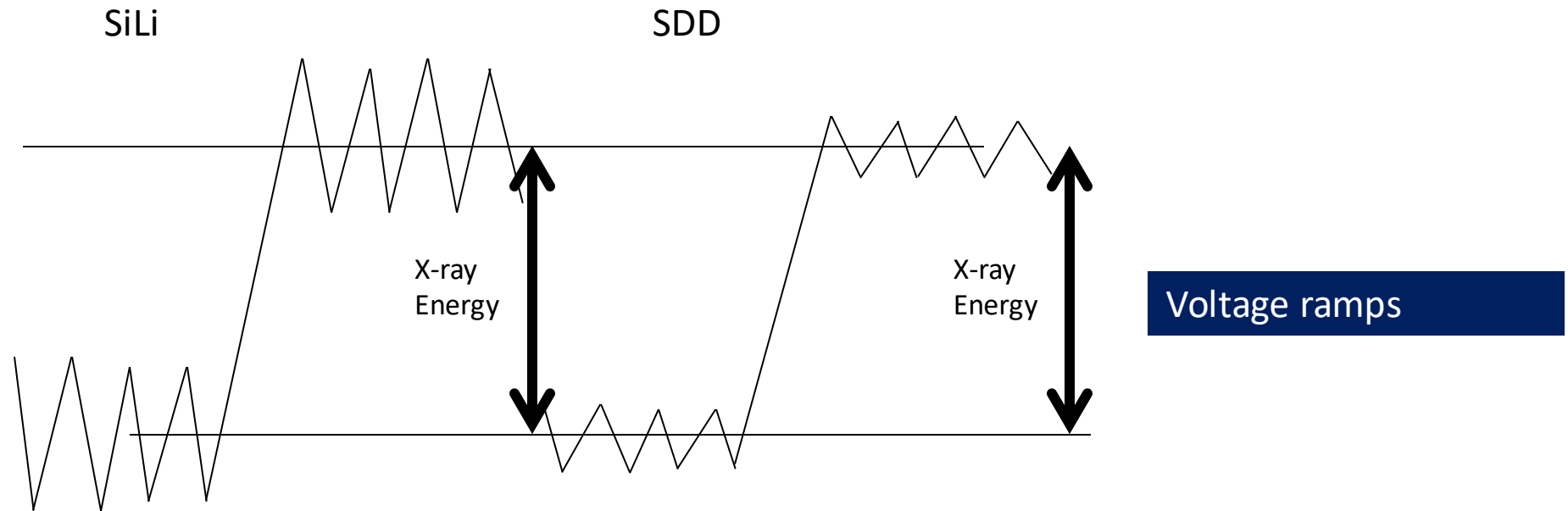
Silicon drift detectors (SDD) created an order of magnitude leap in EDS speed and resolution

1. Liquid nitrogen free
2. Superior resolution
3. Greatly increased count rate



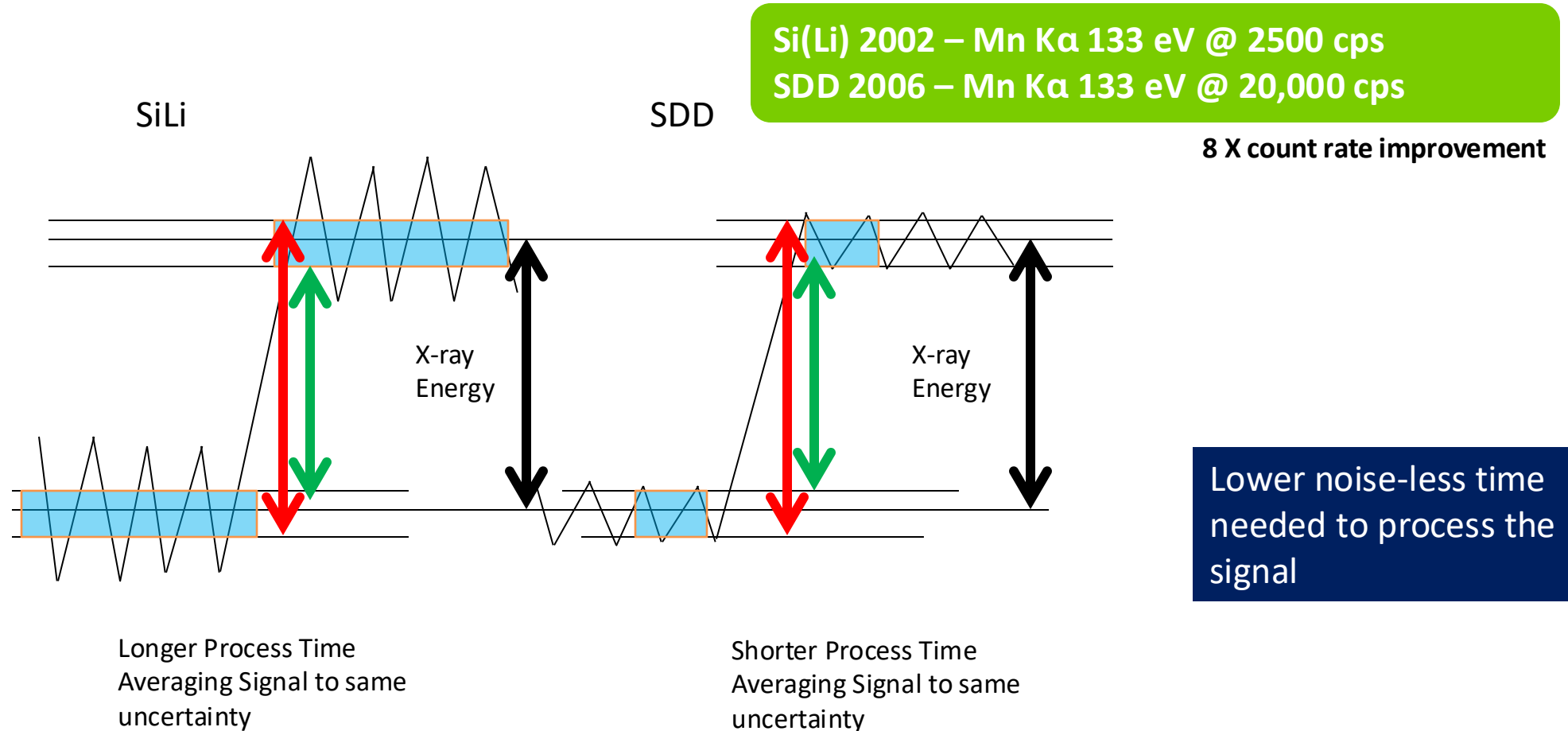
Leaps in EDS Technology: Transition from SiLi to SDD (2000's)

The speed and Resolution benefits of low noise SSD's



Leaps in EDS Technology: Transition from SiLi to SDD (2000's)

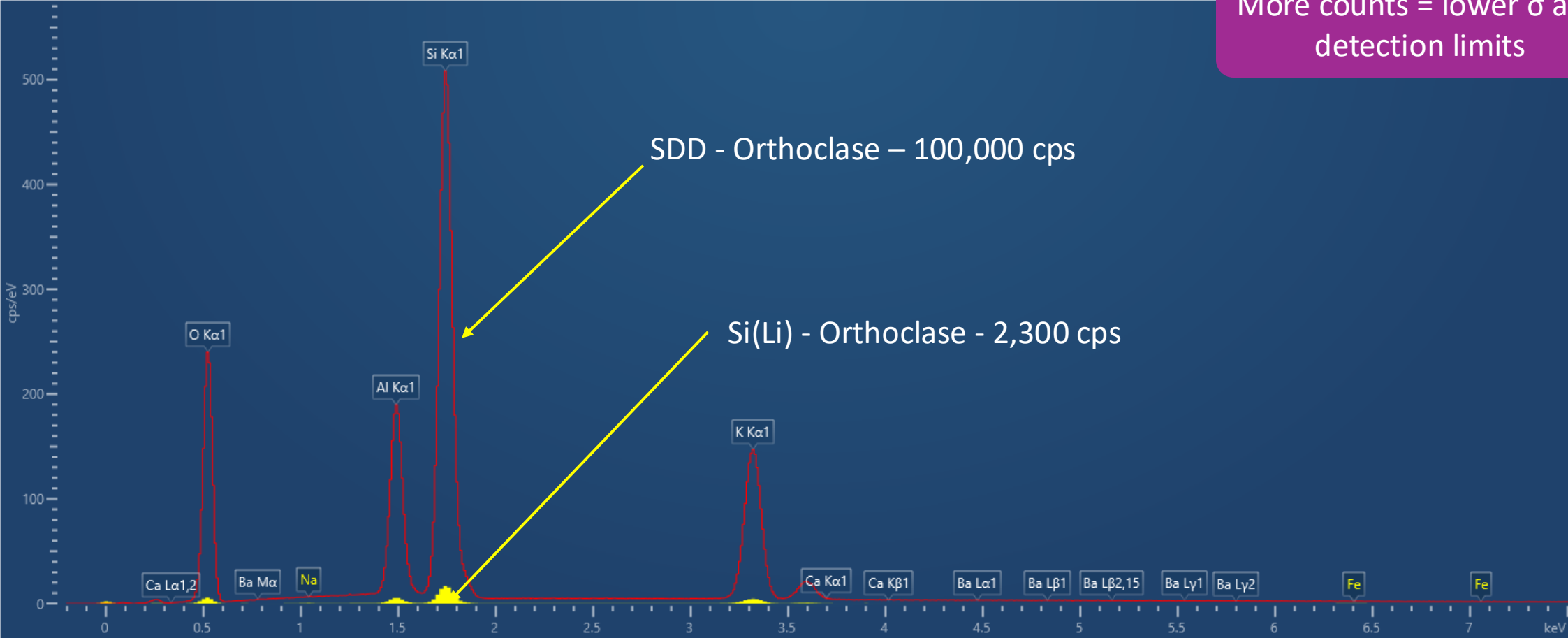
The speed and Resolution benefits of low noise SSD's



Leaps in EDS Technology: Transition from SiLi to SDD (2000's)

The speed and Resolution benefits of low noise SSD's

More counts = lower σ and detection limits



Si(Li) detector would take 40 sec to achieve 100,000 counts

Leaps in EDS Technology: Large Area SDD's (2012)

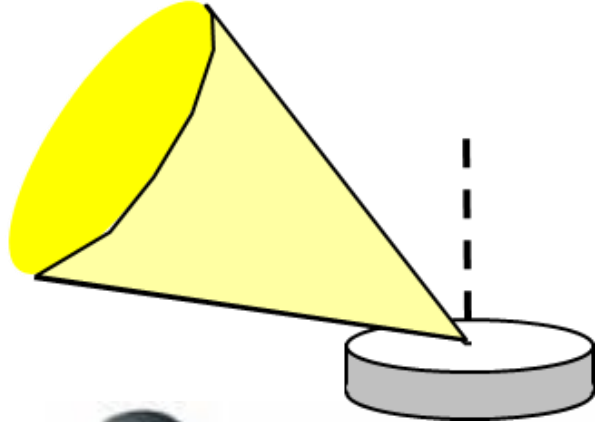
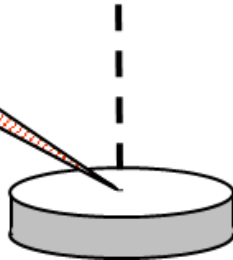
Sensor sizes got larger without compromising resolution

- Low beam current
- Low accelerating voltage
- More counts!

10mm²

X-act – 10 mm²

Mn resolution 133 eV @
20,000 cps



Mn resolution 127 eV @
50,000 cps

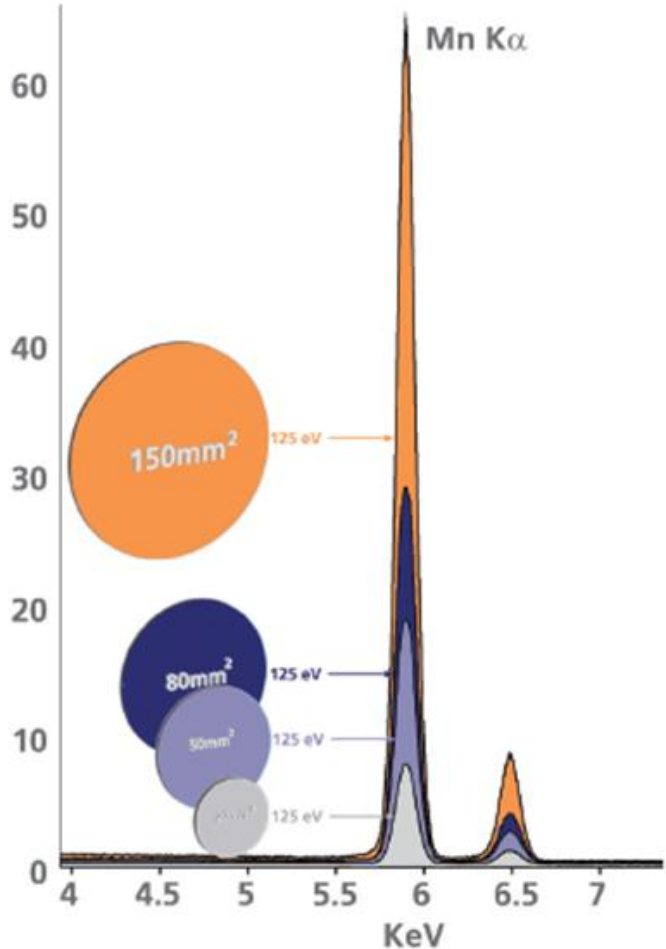
X-MaxN – up to
150 mm²

Leaps in EDS Technology: Large Area SDD's (2012)

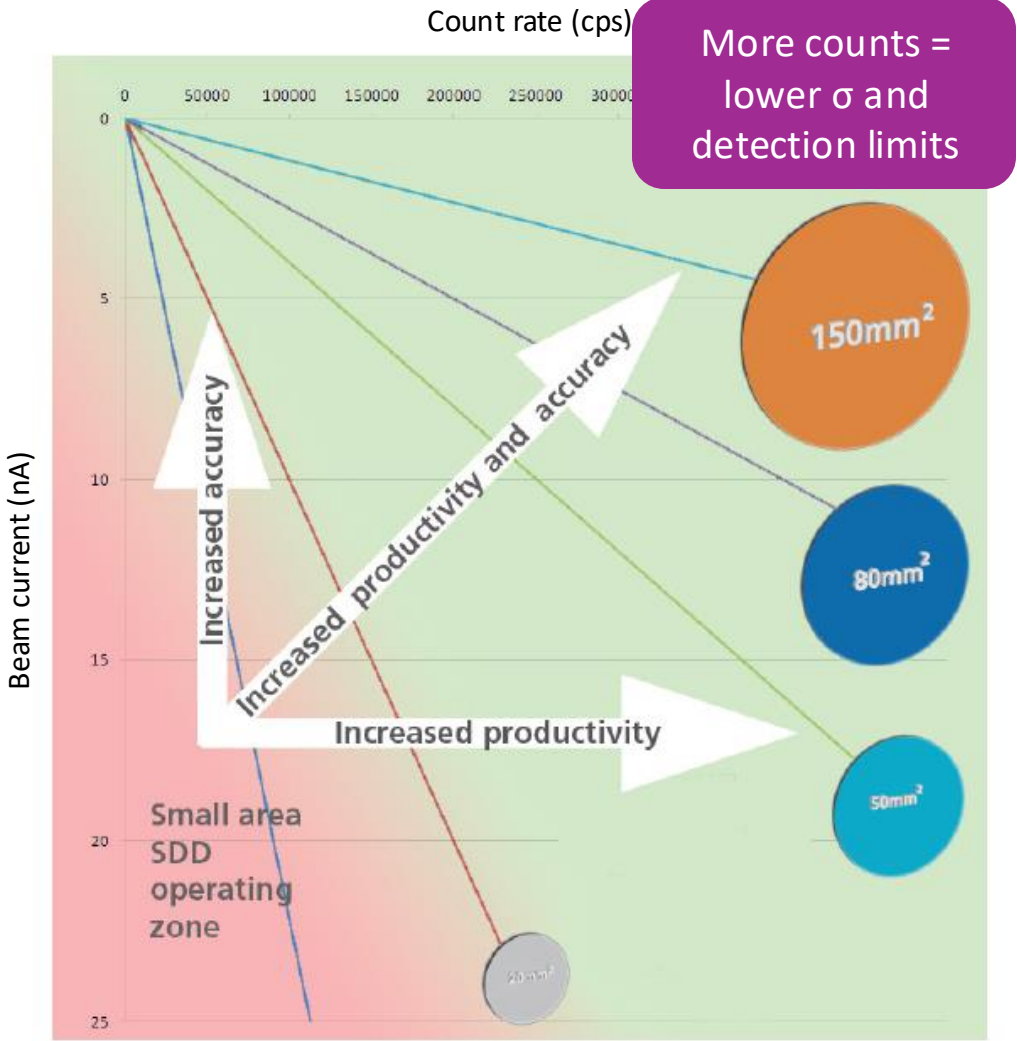
SDD's got larger without compromising resolution

High speed analysis with:

- Low beam current
- Low accelerating voltage



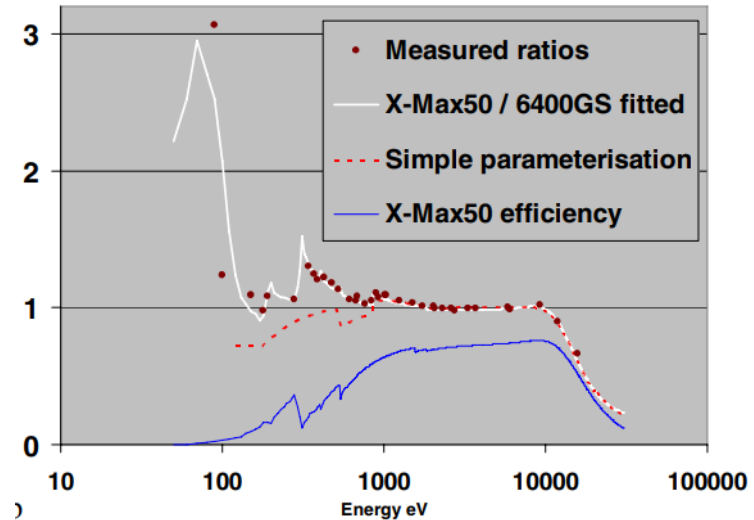
A 150 mm^2 detector requires around 1 nA to generate 100,000 counts per second. In contrast, a 10 mm^2 detector requires >20 nA *



Leaps in EDS Technology: Spectrum Processing (2010's)

Sources of error in 'standardless' quantitative analysis have been drastically reduced

Detector efficiency



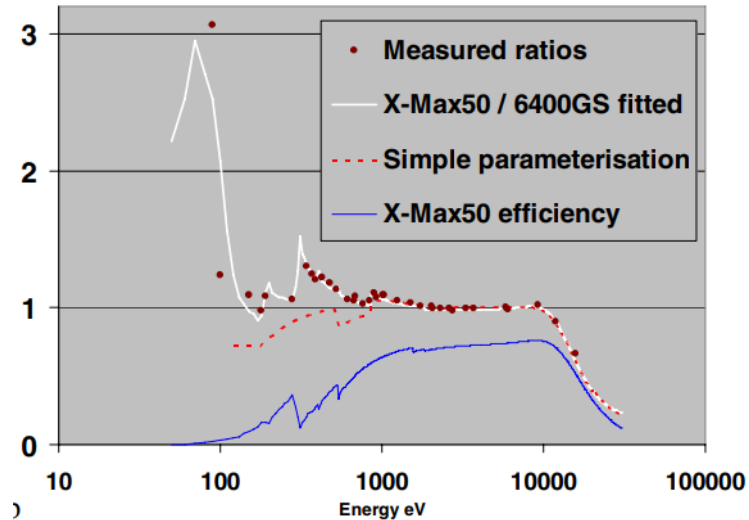
Improved low energy X-ray and light element quantification

Statham, 2010, Statham 2009, Statham 2002, Newbury and Ritchie 2016, Eggert et al., 2012, Statham 2016, Pinaud et al., 2020

Leaps in EDS Technology: Spectrum Processing (2010's)

Sources of error in 'standardless' quantitative analysis have been drastically reduced

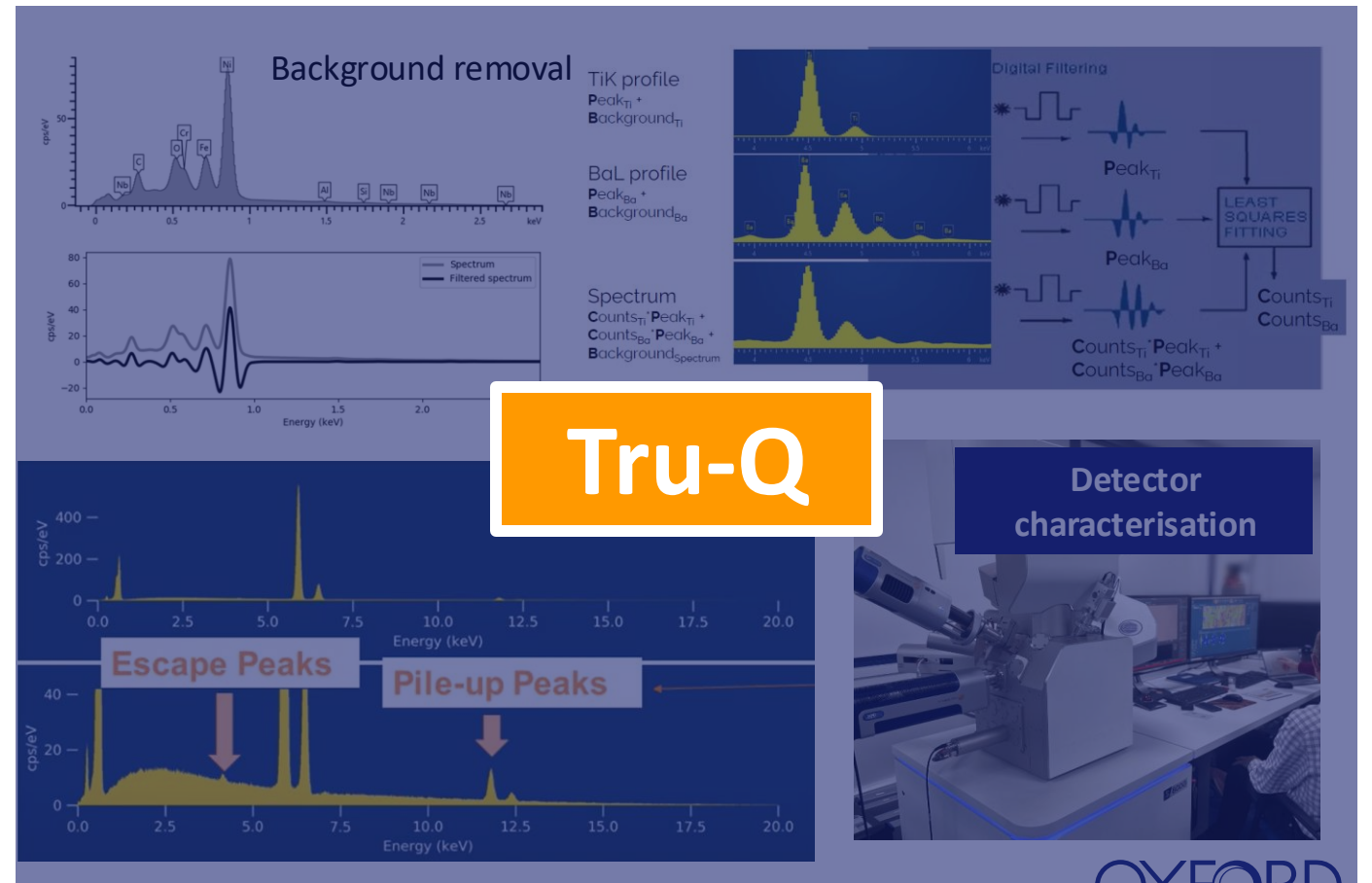
Detector efficiency



Improved low energy X-ray and light element quantification

Statham, 2010, Statham 2009, Statham 2002, Newbury and Ritchie 2016, Eggert et al., 2012, Statham 2016, Pinard et al., 2020

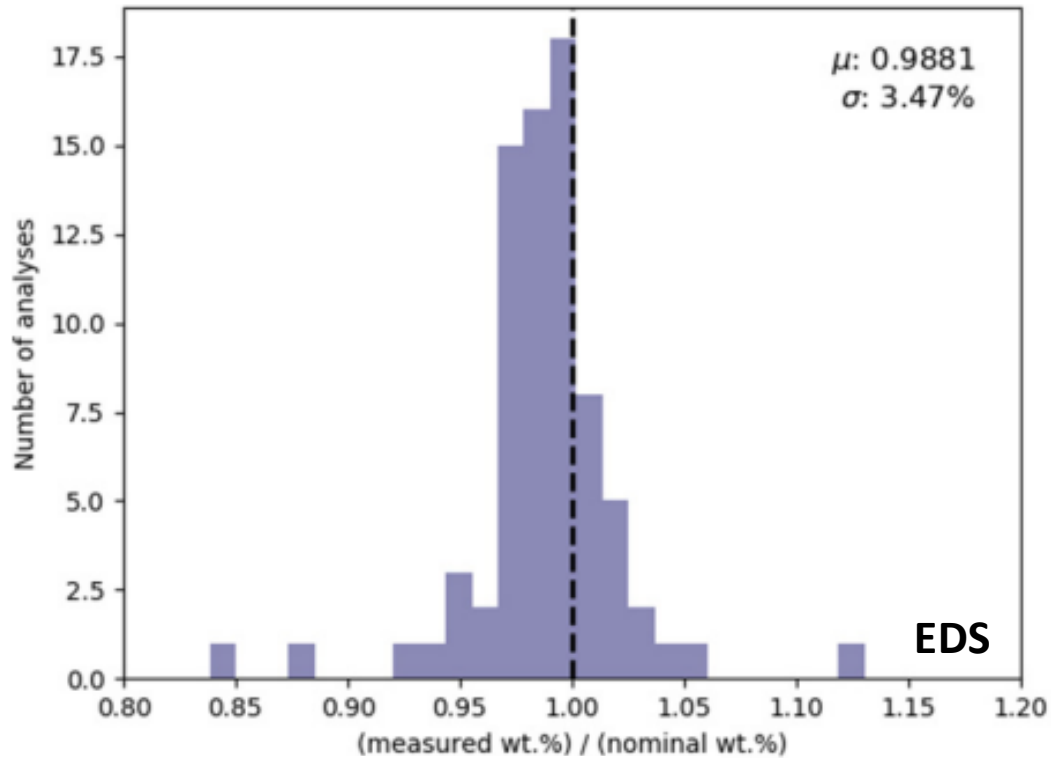
Extracting Accurate X-ray Intensity



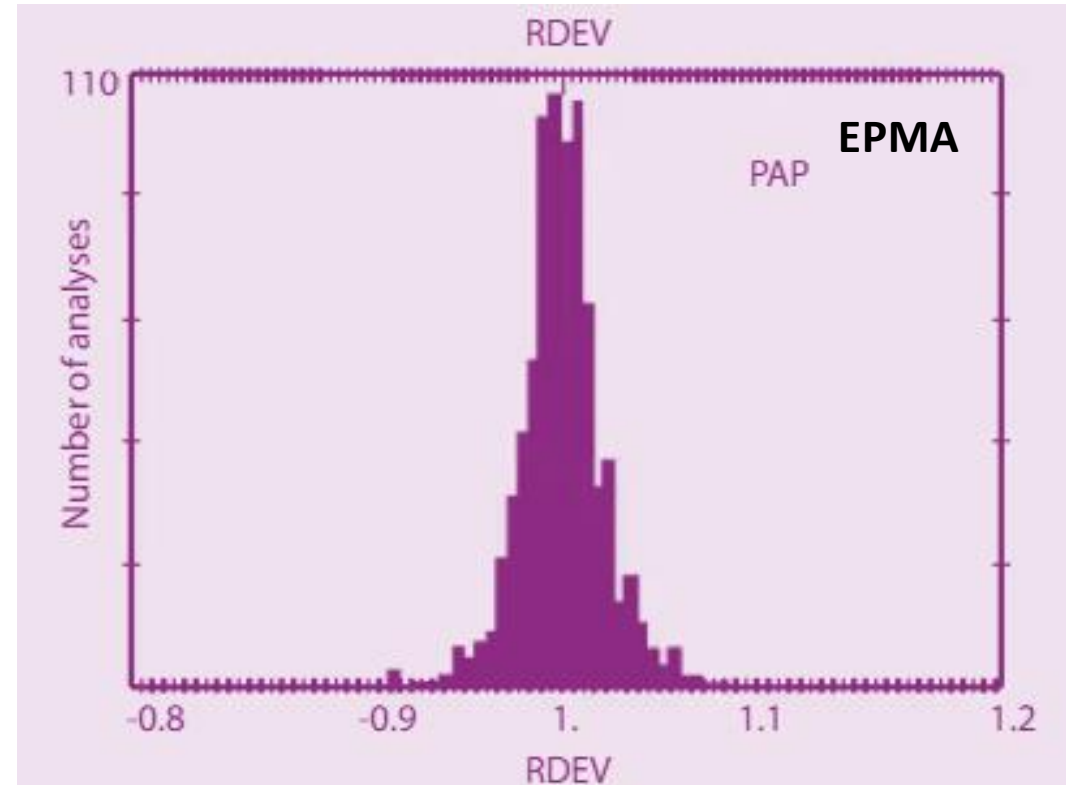
Leaps in EDS Technology: Spectrum Processing (2010's)

Sources of error in 'standardless' unnormalized quantitative analysis have been drastically reduced

20 kV, 50 kcps



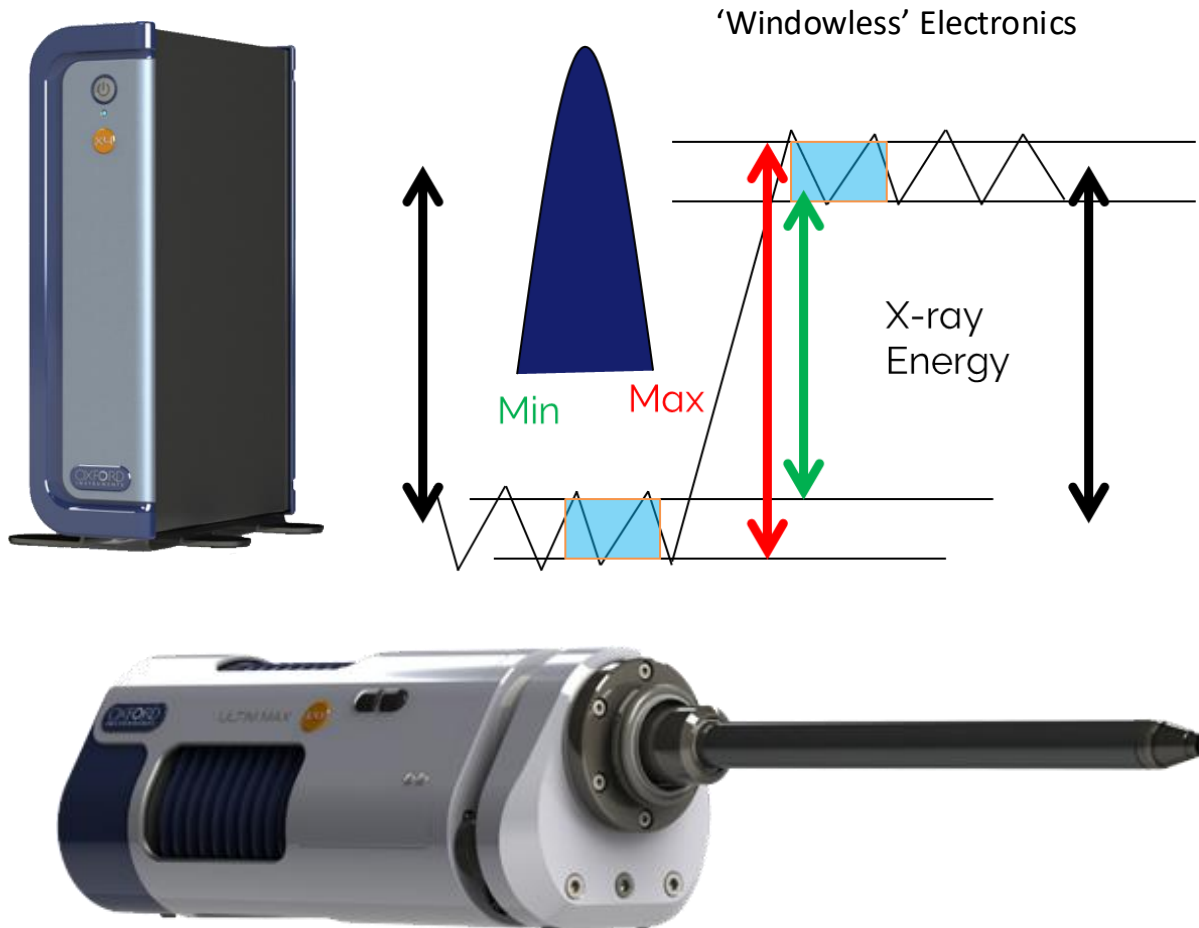
Pinard et al., 2020



Pouchou and Pichoir, 1991

Leaps in EDS Technology: Ultim Max Series EDS (2018)

Ultim Max brought windowless 'low-noise' electronics to the masses, increasing speed



Mn Res.	F Res.	C Res.	@ cps
127eV	64eV	56eV	130,000

Same resolution as X-MaxN with 260% the count rate

Increased speed

More counts

lower σ and detection limits

Tackle more challenging tasks with improved counting statistics:

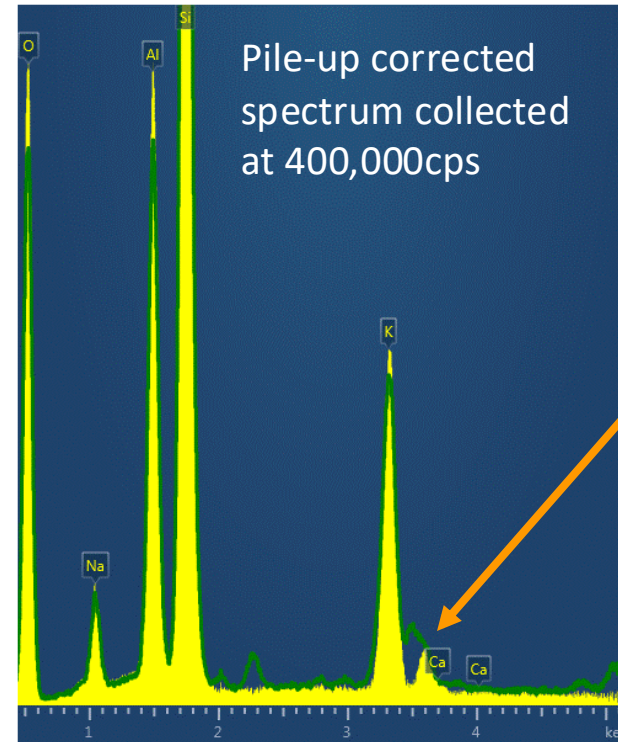
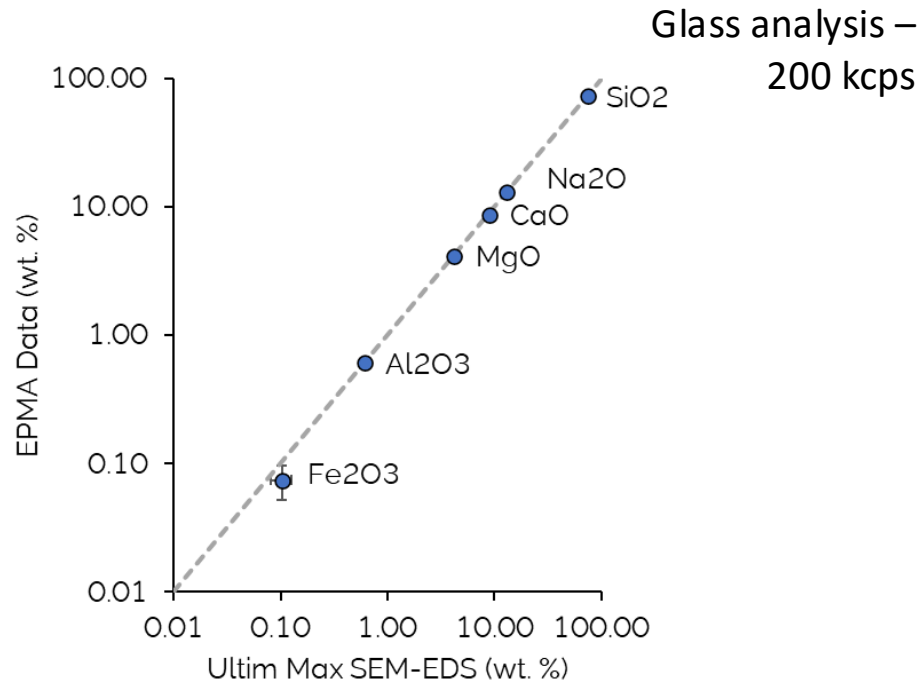
- Minor and trace elements
- Quantification
- Low wt.% variation

Leaps in EDS Technology: Ultim Max Series EDS (2018)

Light, trace & minor elements with speed and reliability

Tackle More Challenging Tasks with Greater Counting Statistics:

- Minor and trace elements
- Quantification



Minor Ca in Orthoclase, large interference from pile-up

Low degradation in resolution with increased count rate

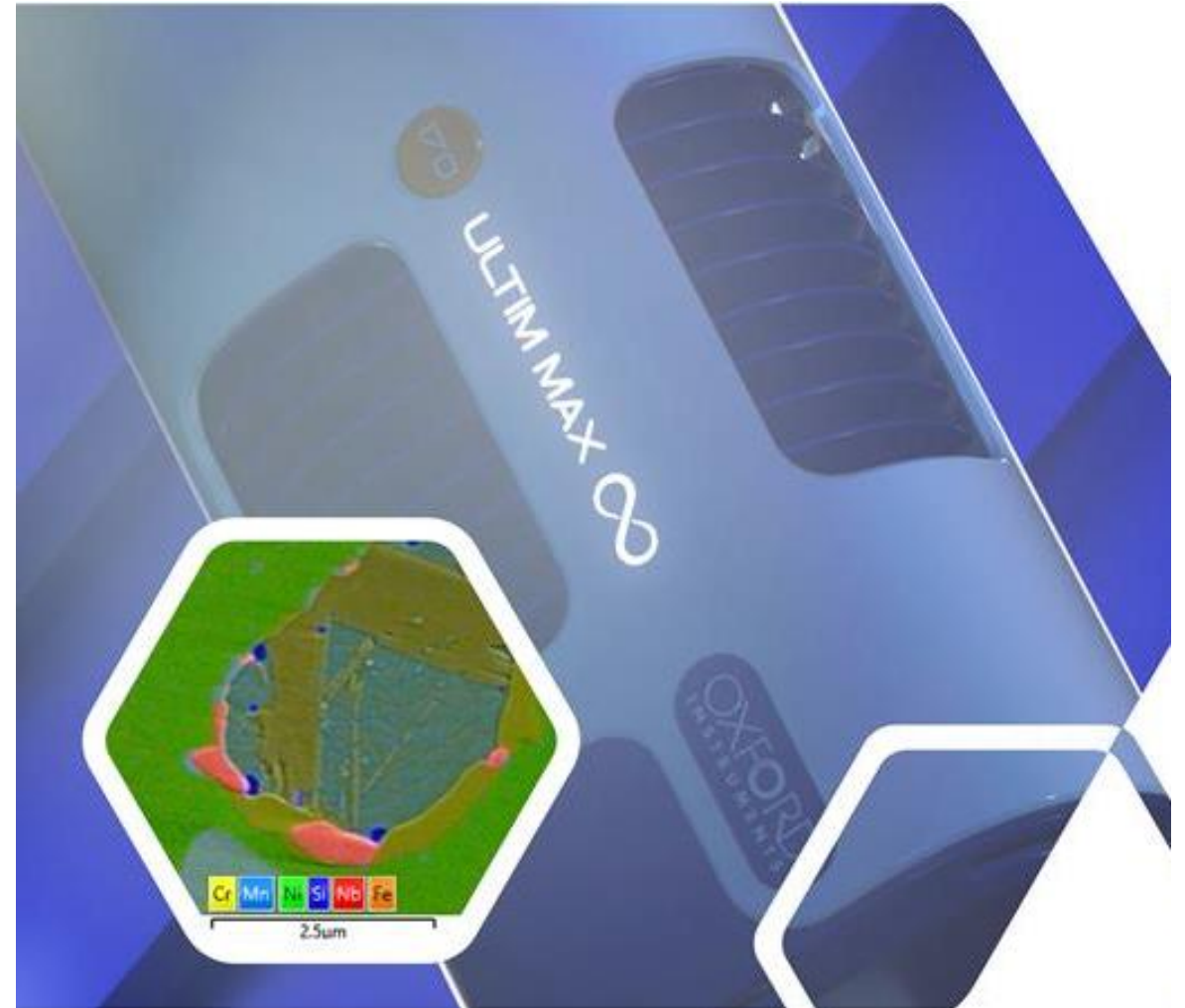
	O	Na	Al	Si	K	Ca
4,000cps	46.68	2.55	9.92	30.56	10.04	0.25
400,000cps	46.71	2.55	9.89	30.62	9.97	0.27

Leaps in EDS Technology: Ultim ∞ series & Tru-Q IQ (2024)

- **New Tru-Q[®] IQ where every detector produces the same high quality, reliable results** solving the most difficult overlaps and finding the most hidden elements
- **Optimisation of the data processing engine to fit the unique performance of every detector**
- **Peak shapes / positions at all energies that fit the collected data, so the smallest signals are revealed**

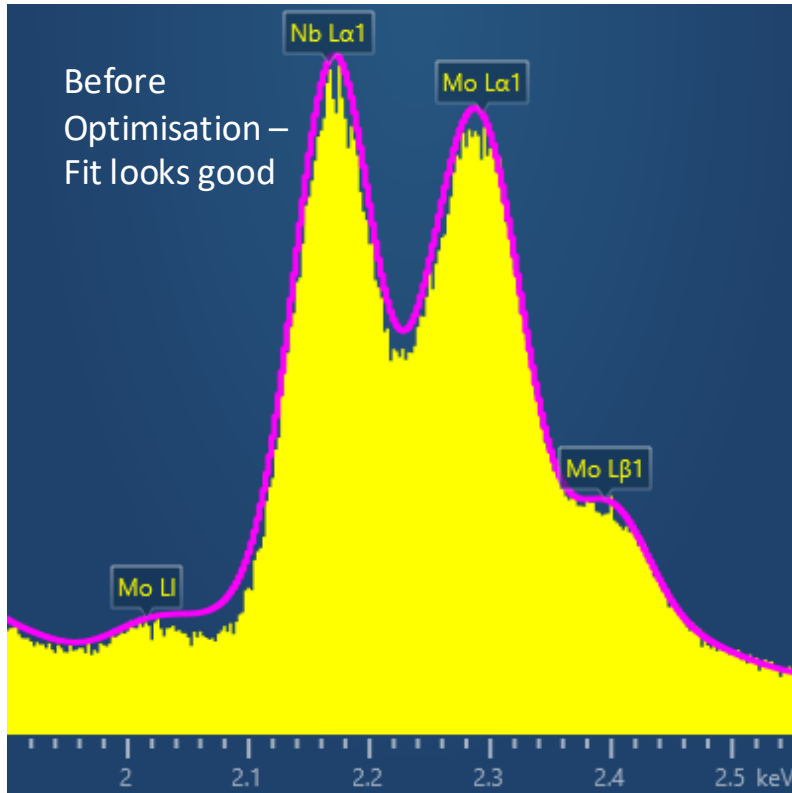
Mn resolution ≤ 127 eV @ 200,000 cps

Same resolution as Ultim with 150% count rate

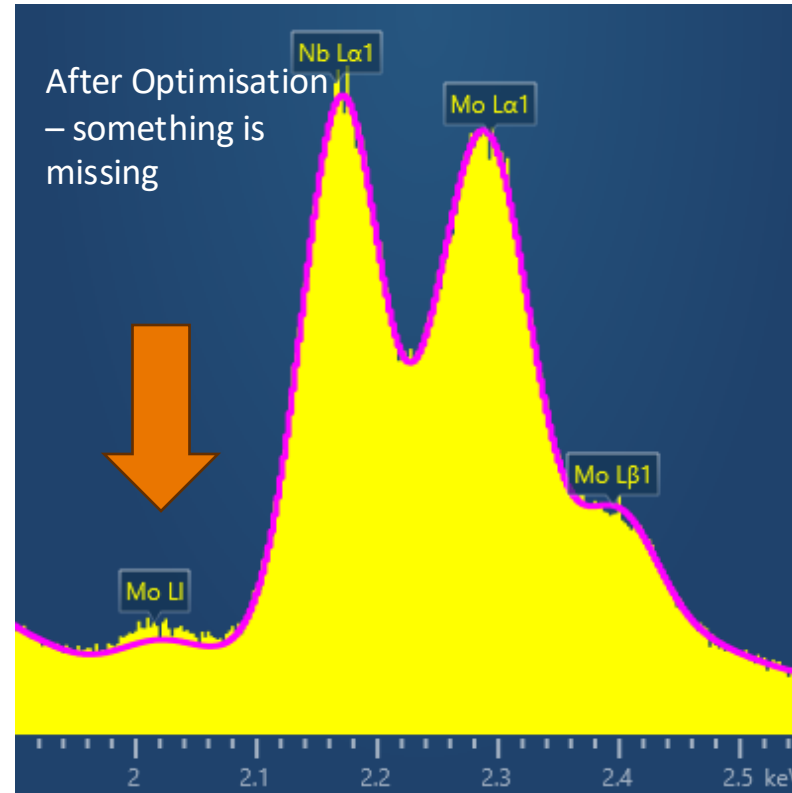


Leaps in EDS Technology: Ultim ∞ series & Tru-Q IQ (2024)

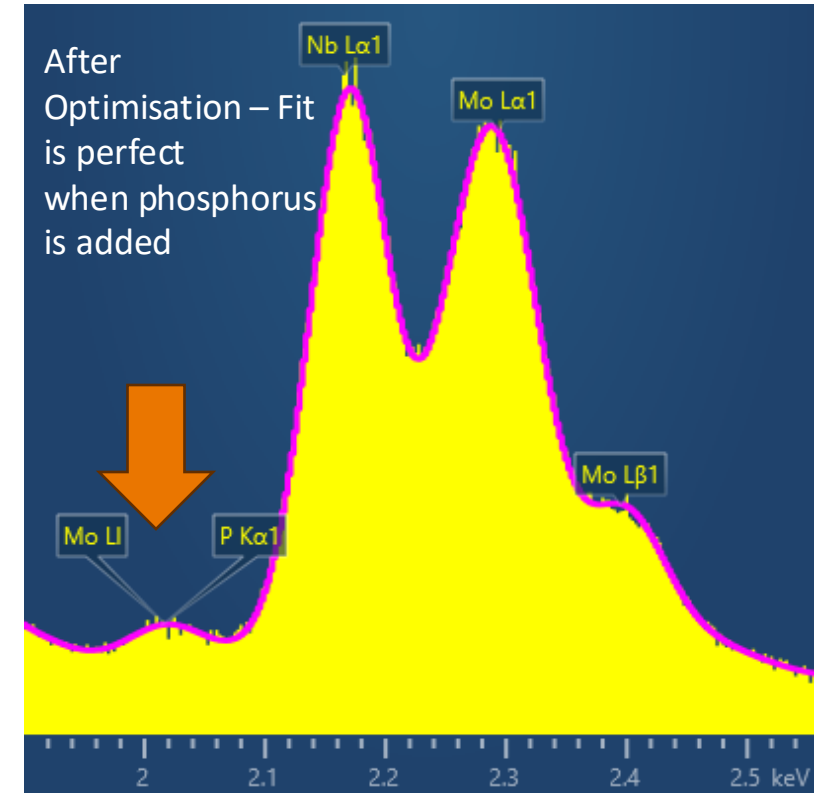
Improved spectrum processing ability with individual characterisation



With Tru-Q IQ every Infinity detector will be able to detect the most hidden element signals.



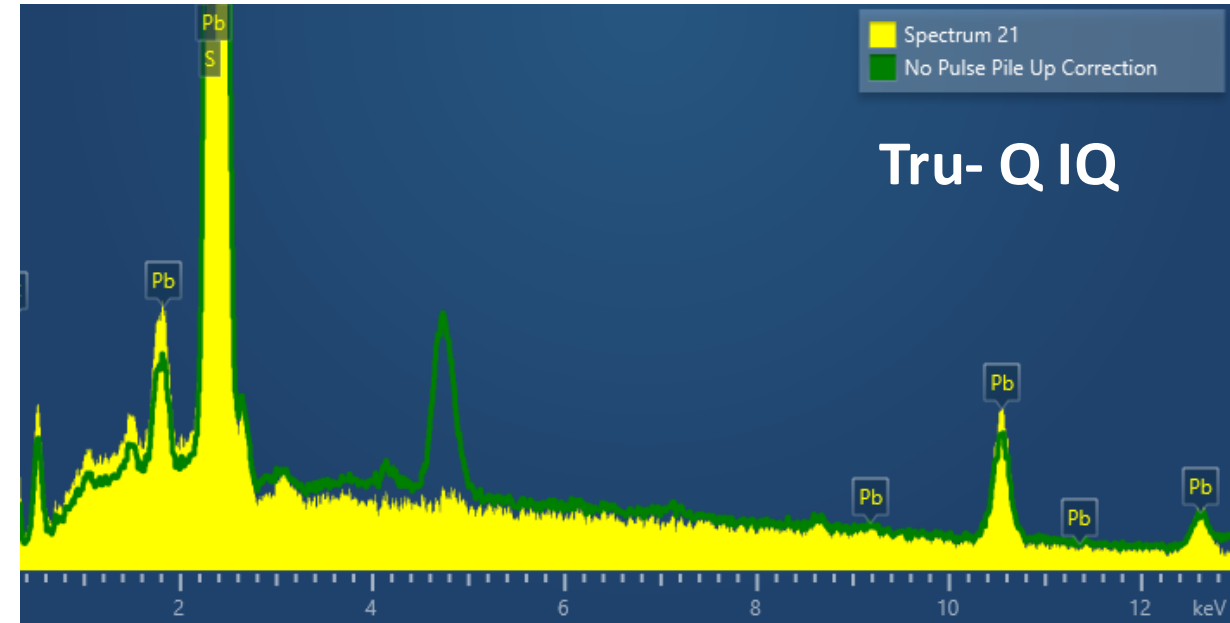
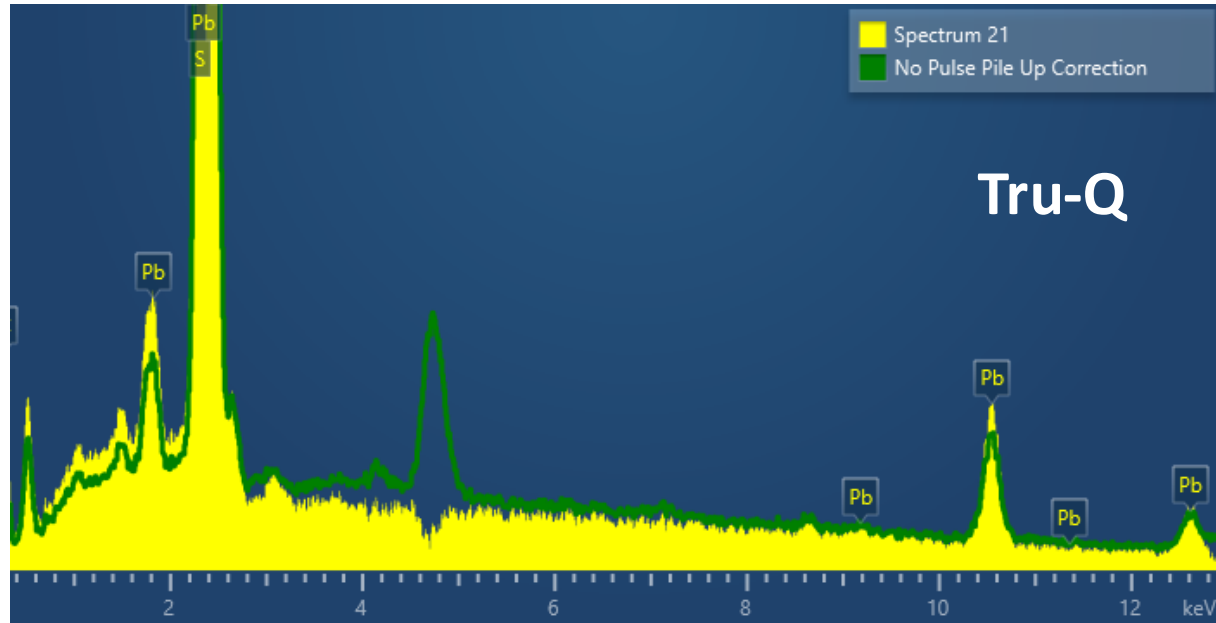
Processing optimised for unique performance of each detector.



- Maintained accuracy at high speeds
- Practical trace and minor element characterisation

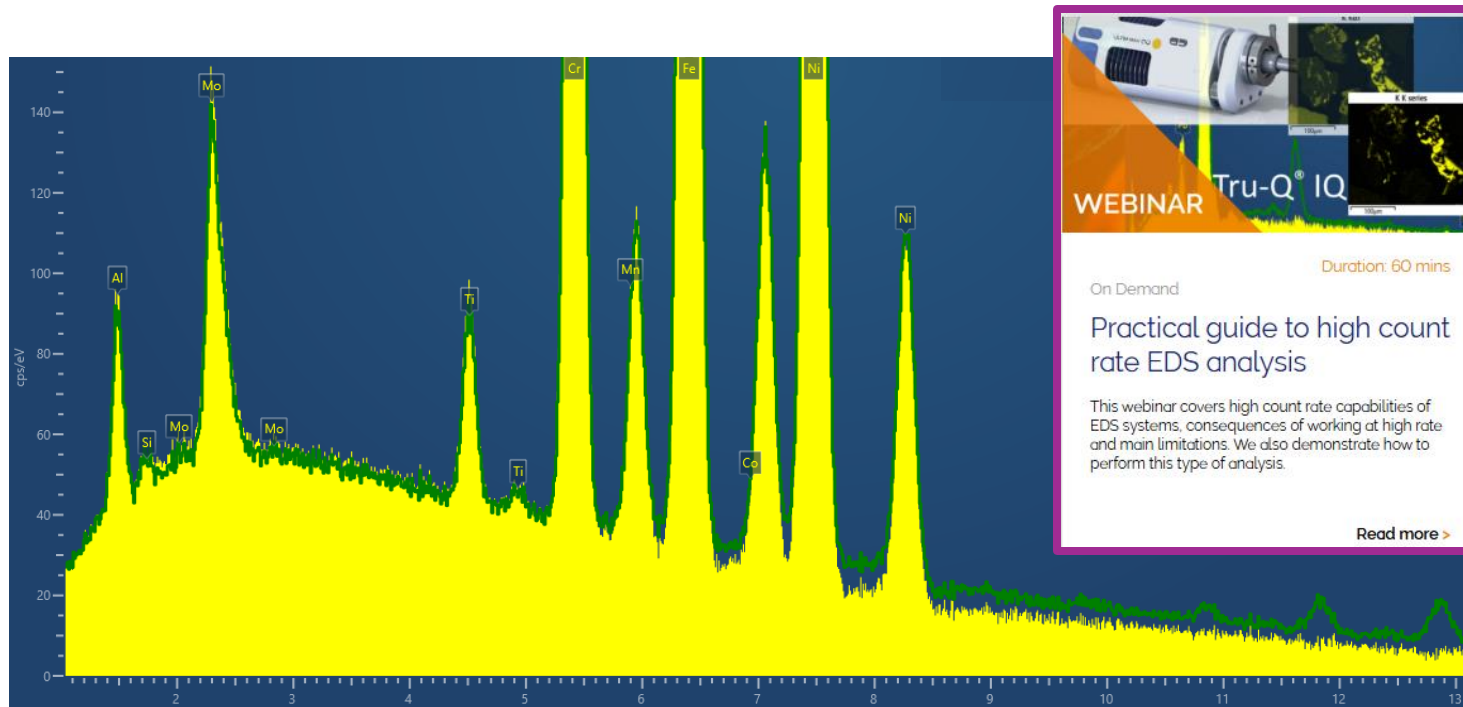
Tru-Q IQ (pile up)

- Example of Pile-up coefficient optimisation (PUC)



Leaps in EDS Technology: Ultim ∞ series & Tru-Q IQ (2024)

Optimal pile up correction gives accurate quant even at high count rate

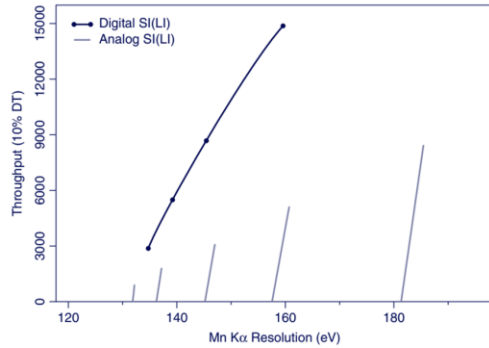


- Un-normalised data
- low and high-count rate data (115 cps vs 840 cps)
- Same quality of the results with different settings

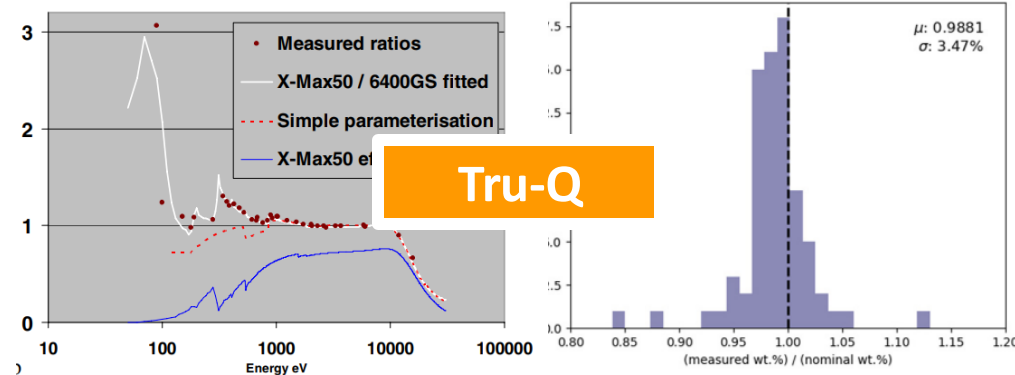
Element	wt% with PPC	wt% without PPC	Diff. (%)
Al	1.3552	1.2381	8.6
Si	0.13	0.14	-10.0
Ti	1.20	1.10	7.9
Cr	17.92	16.54	7.7
Mn	0.03	0.00	93.1
Fe	34.32	31.52	8.2
Co	0.10	0.09	6.5
Ni	42.65	39.16	8.2
Mo	3.44	3.18	7.5
Total	101.14	92.97	

Summary: How EDS Closed the Gap to WDS

Digital Spectrum Processing



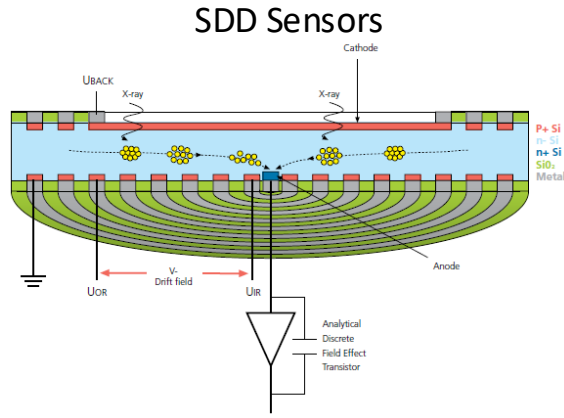
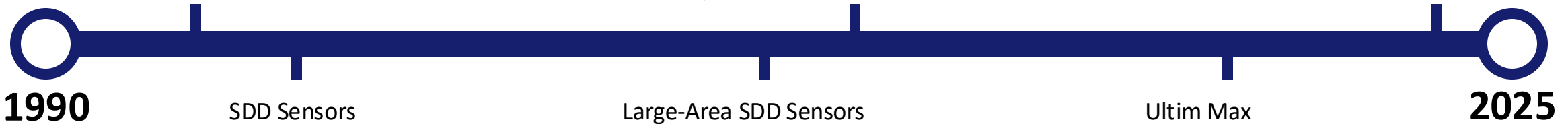
Speed – resolution - stability



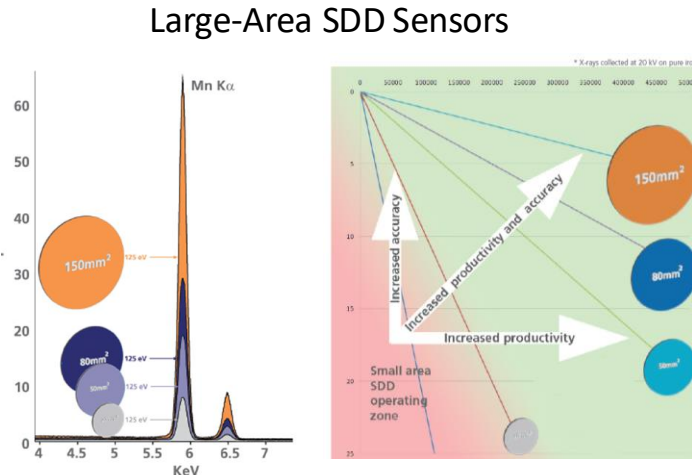
Accurate & repeatable spectrum processing for major, minor and traces



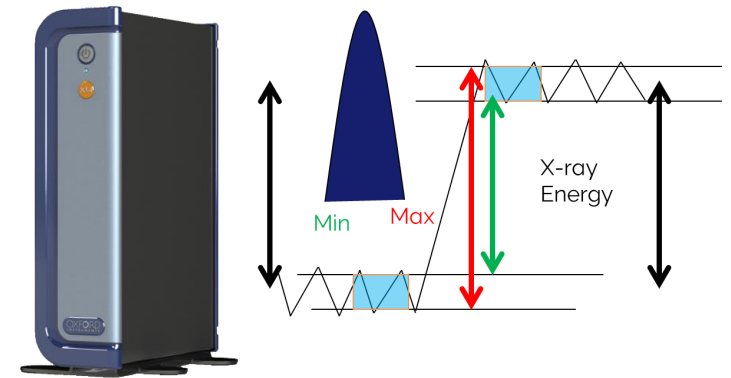
Further noise reduction, advanced pile-up correction and individual optimization



Reduced noise – higher count rates



More counts – same resolution – lower currents



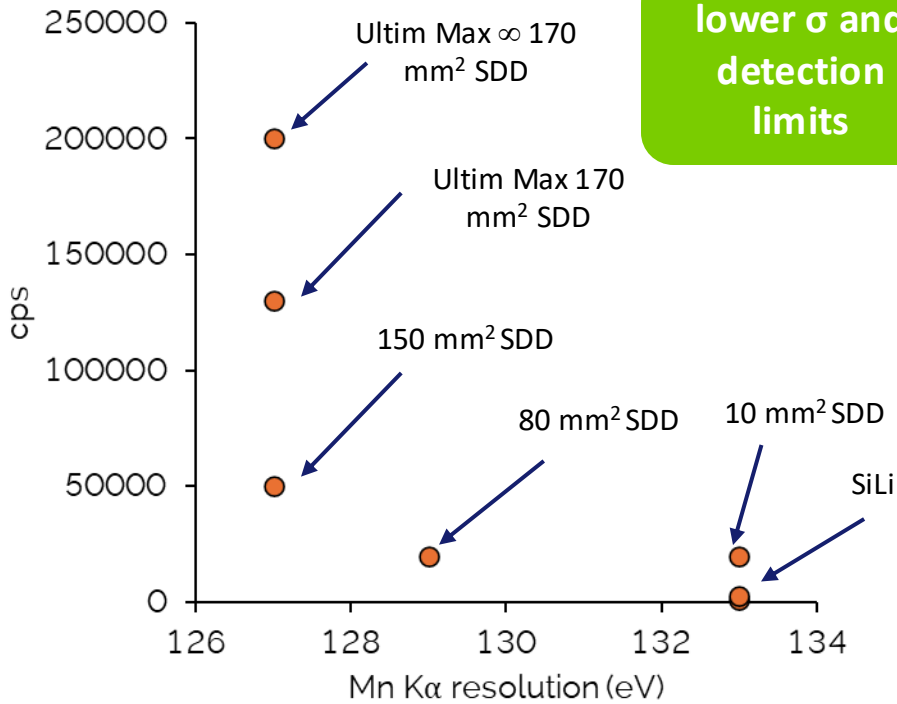
Reduced noise - higher count rates

Summary: How EDS Closed the Gap to WDS

Spectral Resolution and Speed

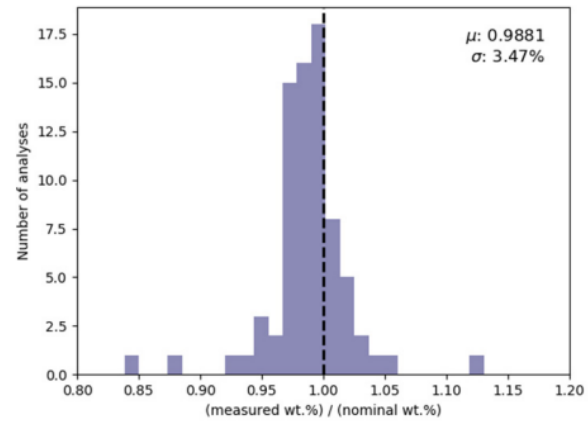
Generate lots of counts in far less time!!

lower σ and detection limits

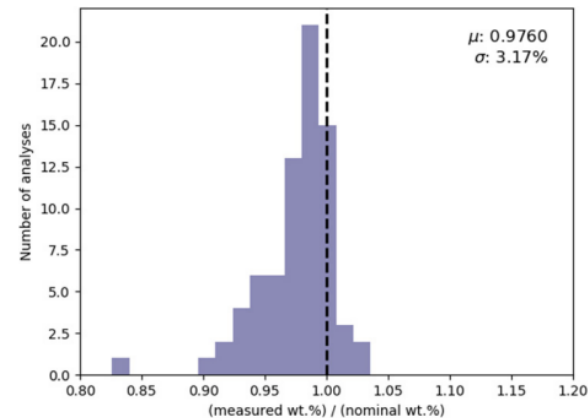


Accuracy and Precision

20 kV, 50 kcps



20 kV, 200 kcps



Detection limits

In the 100's of ppm

- Estimated using 3σ and synthesised spectrum
- Dependent on the matrix and kV

Detection Limit in Steel – 20 kV – 100 M counts			
Element	Wt. %	Wt. % σ	Detection limit (3 X wt.% σ)
Ti	1	0.004	0.012

Bulk (wt.%), Ni = 8, Fe = 70, Mn = 2, Cr = 19, Ti = 1

How to Achieve These Results

Realising WDS data quality thanks to modern EDS technology (in practice...)



Best practice workflow

Recommended Workflow for Quantitative Analysis

OXFORD
INSTRUMENTS

Contact us:



Introduction

- Within AZtec 'standardless' method is the default method for quantitative analysis, and if used in conjunction with the Oxford Instruments Recommended Workflow, it will give fast, accurate results for all but the most challenging and complex samples.
- This recommended workflow describes several considerations that are important for ensuring that quantitative analysis gives the correct results.

1

Sample preparation and stage setup

- Align any samples/standards so that they are at the same height on the stage
- Samples should be flat, polished, conductive (e.g. C coating)
- Load a pure metal (e.g. Cu, Co, Mn, Si) for beam measurements



2

SEM and EDS setup

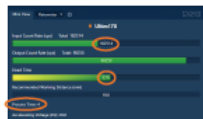
- Check and set the recommended WD for your system
- Set the accelerating voltage (20 kV recommended for standardless microanalysis)
- Remove lens hysteresis
- Use the stage Z position to bring the sample into focus



3

SEM analytical conditions

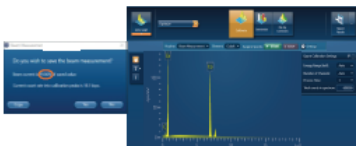
- Adjust beam current to achieve:
 - Input count rate between 60 and 200 kcps
 - Set process time (PT) to between 3-0 and ensure dead time is ~60% or below



4

Beam measurement - for un-normalised quant

- Perform a beam measurement on the pure metal
- Check focus (adjust stage Z)
- Set magnification to >10,000x
- Use same accelerating voltage and beam current for the beam measurement and the unknown sample
- Check beam current stability during your session



5

Measuring the sample

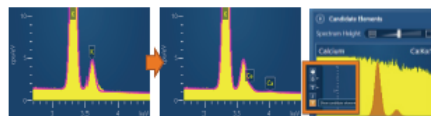
- Enter appropriate coating information
- High magnification (e.g. >10,000x)
- EDS Acquire Spectrum settings:
 - Set count limit to 1,000,000 counts
 - Ensure Pulse Pile Up Correction is on



6

During/post acquisition

- Verify element AutoID is correct
- This can be done using:
 - Fitted spectrum (pink)
 - Analytical total, normally 100% ± 2% (unnormalised analysis)
 - Load a pure metal (e.g. Cu, Co, Mn, Si) for beam measurements



7

During/post acquisition

- Use 'Calculate Composition' to view and interrogate the result
- Check the quant settings
- Processing options
 - Normalised vs. Un-normalised
 - Select the appropriate quant standardisations database - Factory or User



Tip: Quant standardisation for 10-20 kV
Quant standardisation 15 kV and for 5-10 kV

Watch on demand

Quantitative EDS Explained: How to achieve great results

Quantitative EDS Explained: How to achieve great results

Webinar: Watch on demand

This webinar explains the science behind the Oxford Instruments technologies and algorithms, as well as, how to achieve accurate, un-normalized quantitative results using an Oxford Instruments EDS system and the 'standardless' approach. Additionally, the use of EDS to produce high-quality results using Oxford Instruments software with a standard-based method will be explained, with published examples from the field of Earth Science.

Key learning objectives:

- The science and methodology behind EDS analysis and data processing
- The Oxford Instruments approach to 'standardless' quantitative EDS analysis
- How to achieve excellent results and validate the quantitative analysis obtained from your SEM-EDS system

View the webinar on demand

Watch now



Presenter: Dr Rosie Jones

Dr Rosie Jones graduated with a BSc and MSc in GeoSciences and Geochemistry from the University of Leeds, and a PhD in Geology from the University of Edinburgh. She joined Oxford Instruments in 2019 after completing a postdoctoral research position at the University of Oxford. Rosie has always worked with a strong focus on (micro)analytical techniques, including SEM-EDS, EPMA, XRF and mass spectrometry. She is currently Product Manager for WDS and works within the X-Ray Products Team.



Presenter: Dr Simon Burgess

Dr Simon Burgess graduated with a PhD from Edinburgh University. He joined Oxford Instruments in 1997 and has always worked with a strong focus in product management and development. Simon has focused his research on the development of EDS and WDS systems, in particular hardware such as large area SDD and Extreme ultra-high sensitivity detectors. He is currently working as a business manager for EDS and WDS within the product marketing team.

WEBINAR

OXFORD
INSTRUMENTS

Application examples



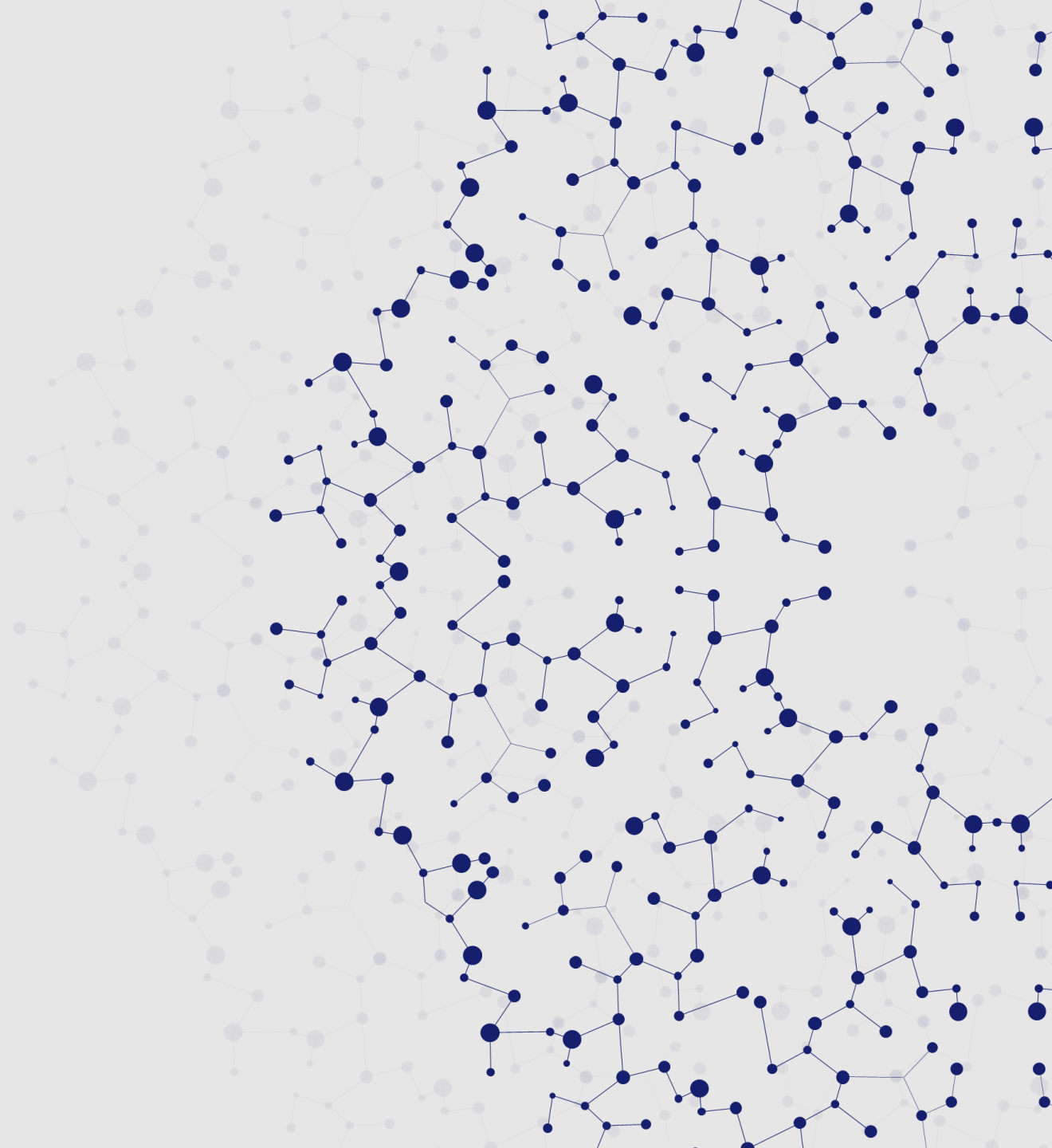
Summary SEM-WDS Applications

WDS major application areas

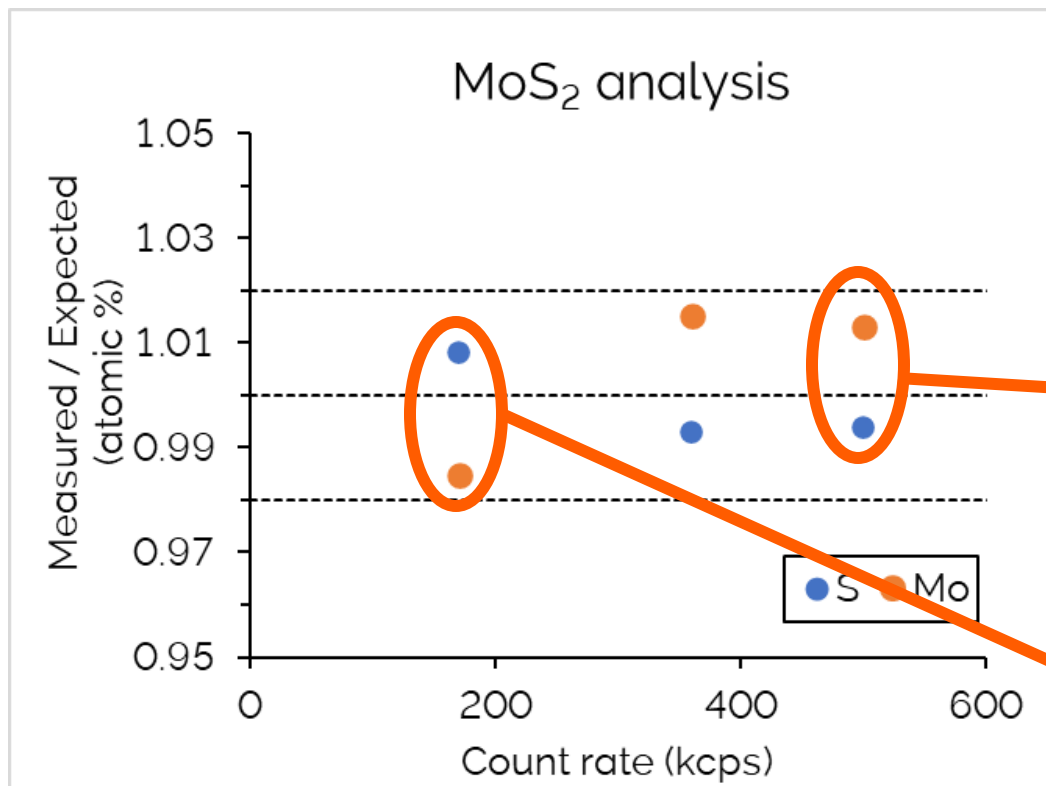
- Analysis of difficult spectral overlaps
- Characterisation of minor and trace elements
- High precision and high accuracy quantitative analysis
- Minor-trace element mapping

Solving Peak Overlaps

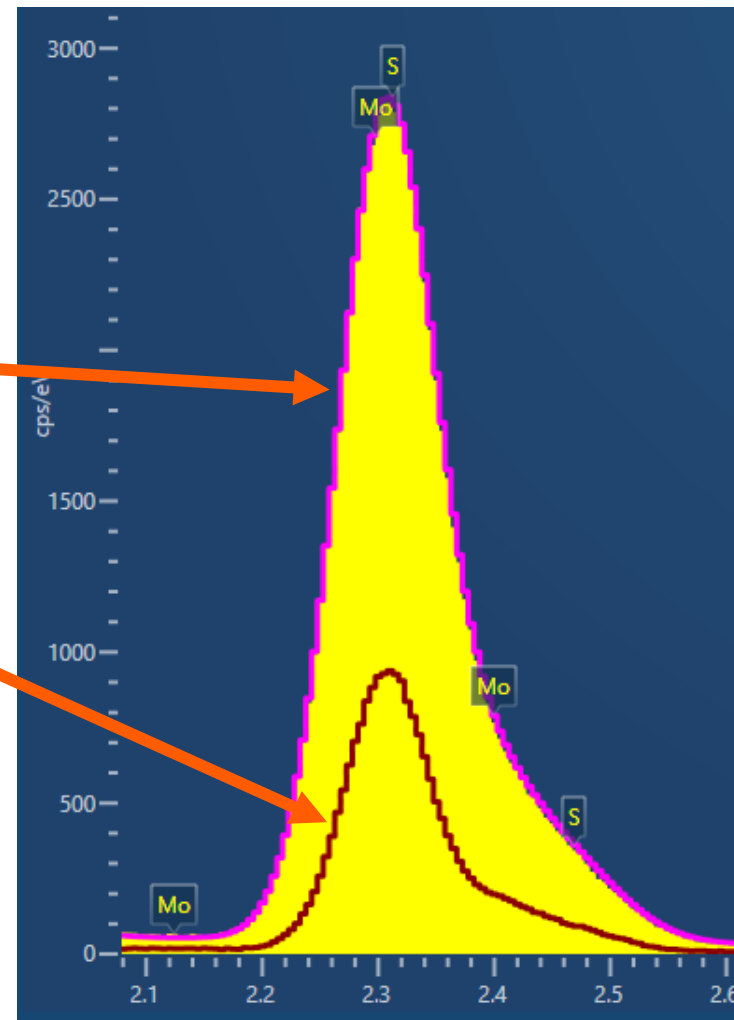
Deconvoluting Mo and S in MoS₂



Solving Peak Overlaps: MoS₂



Count rate (kcps)	Atomic %	
	S	Mo
170	67.21	32.79
380	66.19	33.81
500	66.26	33.74

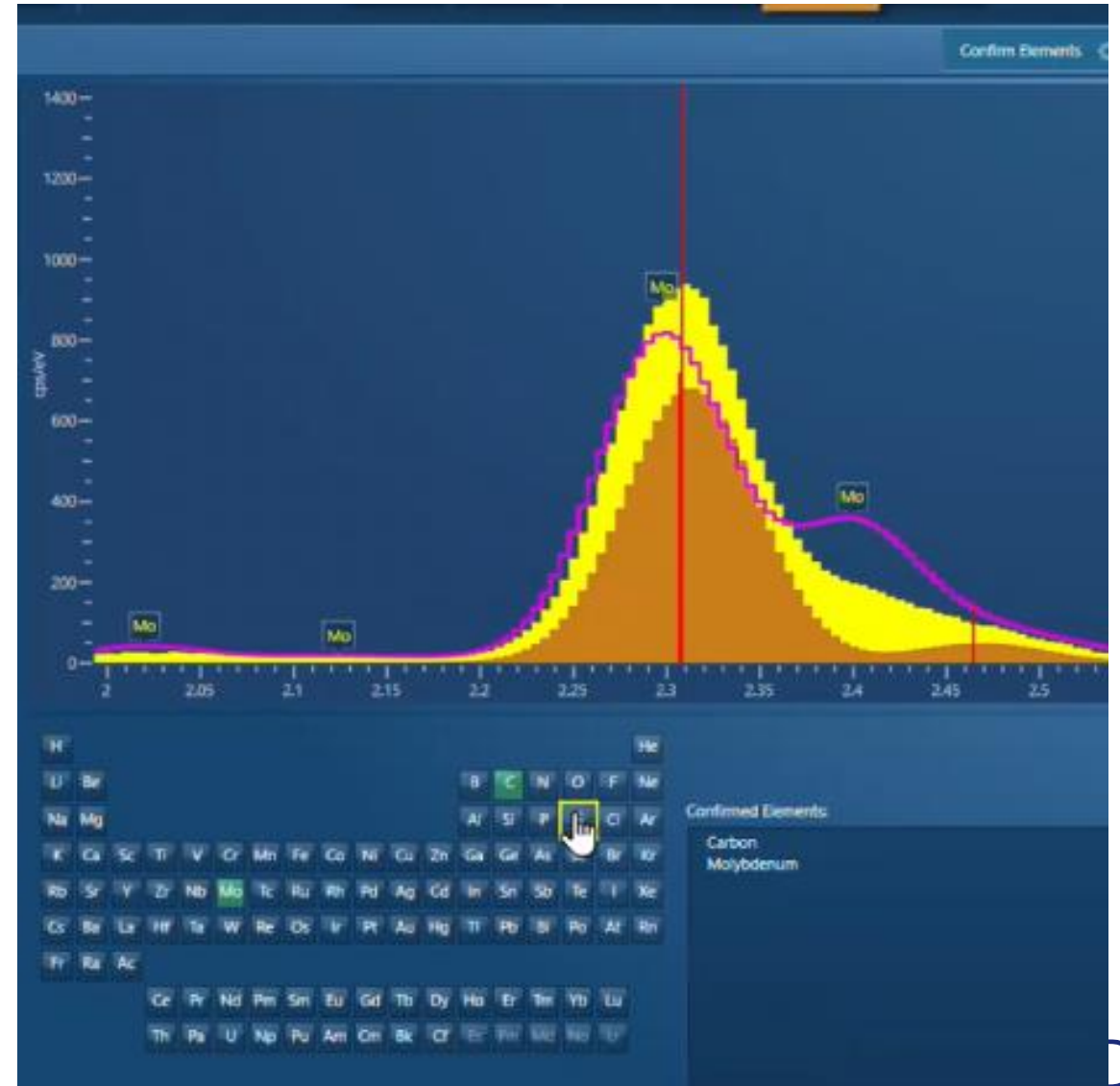


S K α = 2308 eV
Mo L α = 2293 eV

15 eV offset

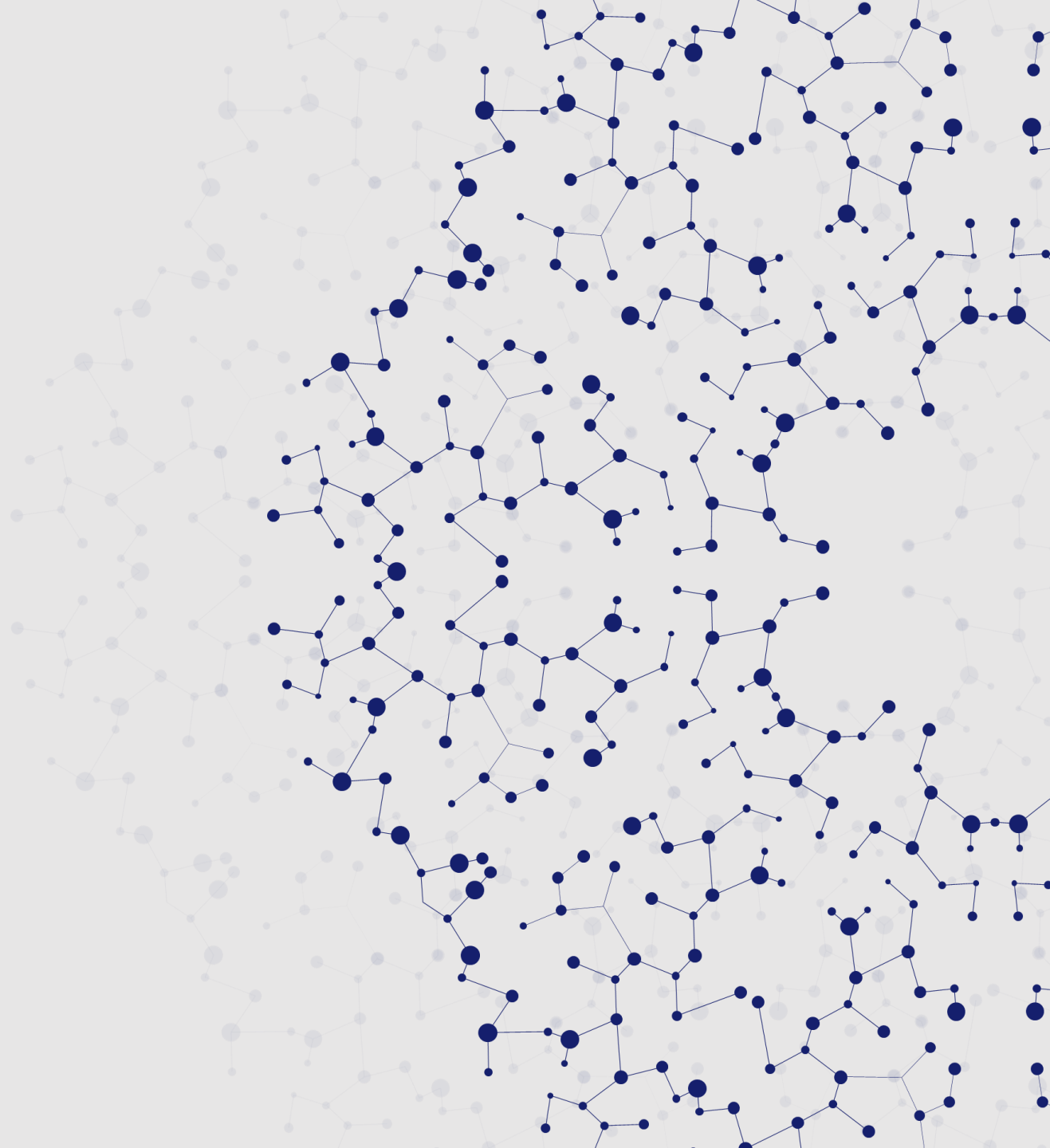
< 2% deviation from
expected in 2
seconds

Solving Peak Overlaps: MoS₂



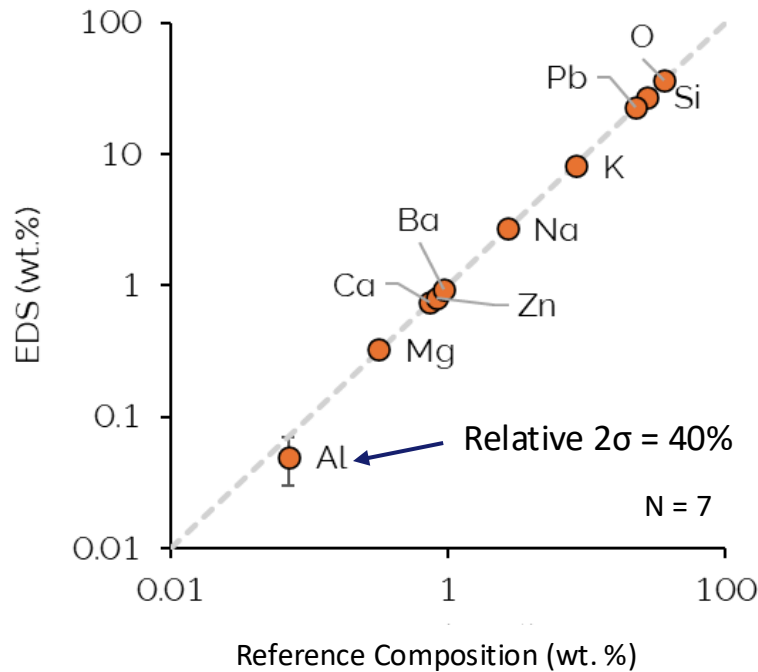
Trace Element Quantification

Quantifying glass trace elements in the 100's ppm

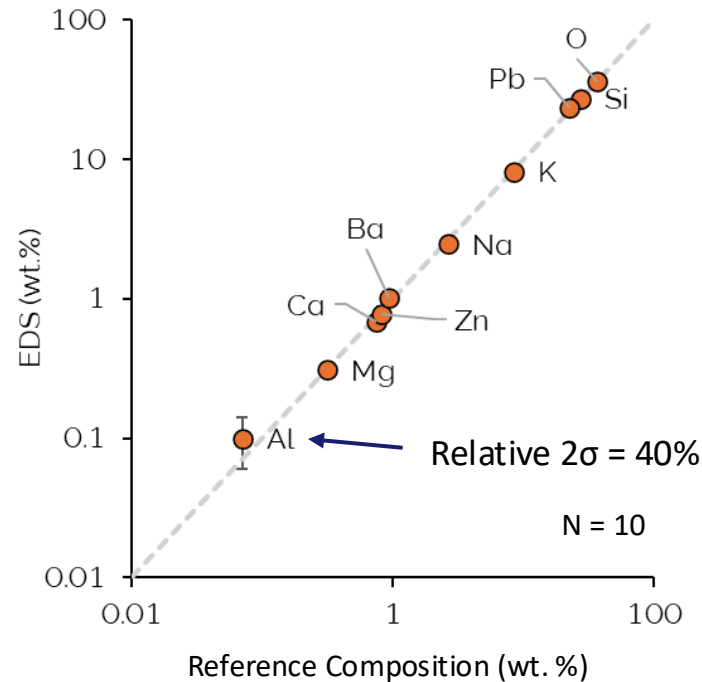


Glass Standard Quantification: Majors, Minors and Traces

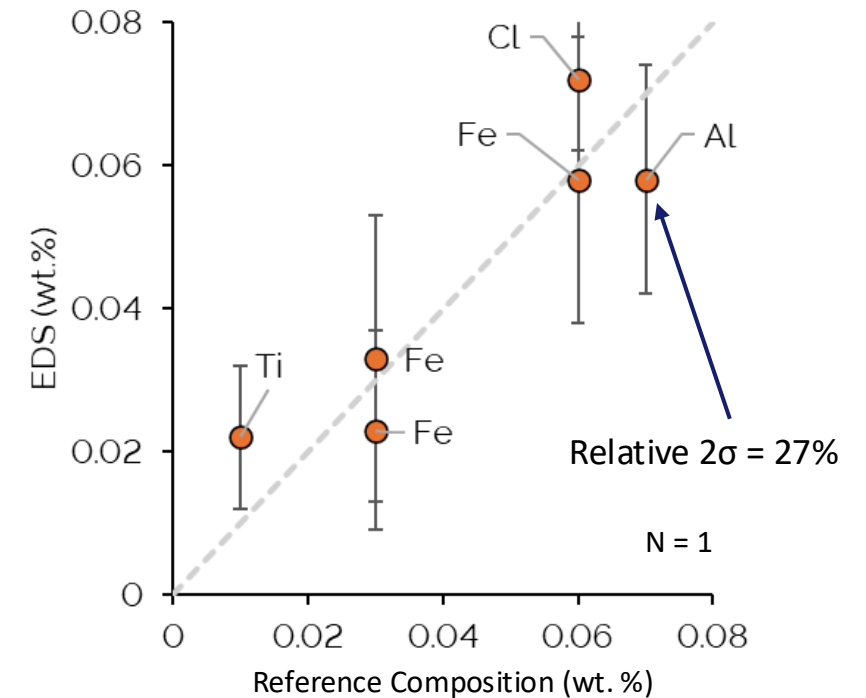
BCR – 165 kcps – 2 M counts



BCR – 670 kcps – 2 M counts



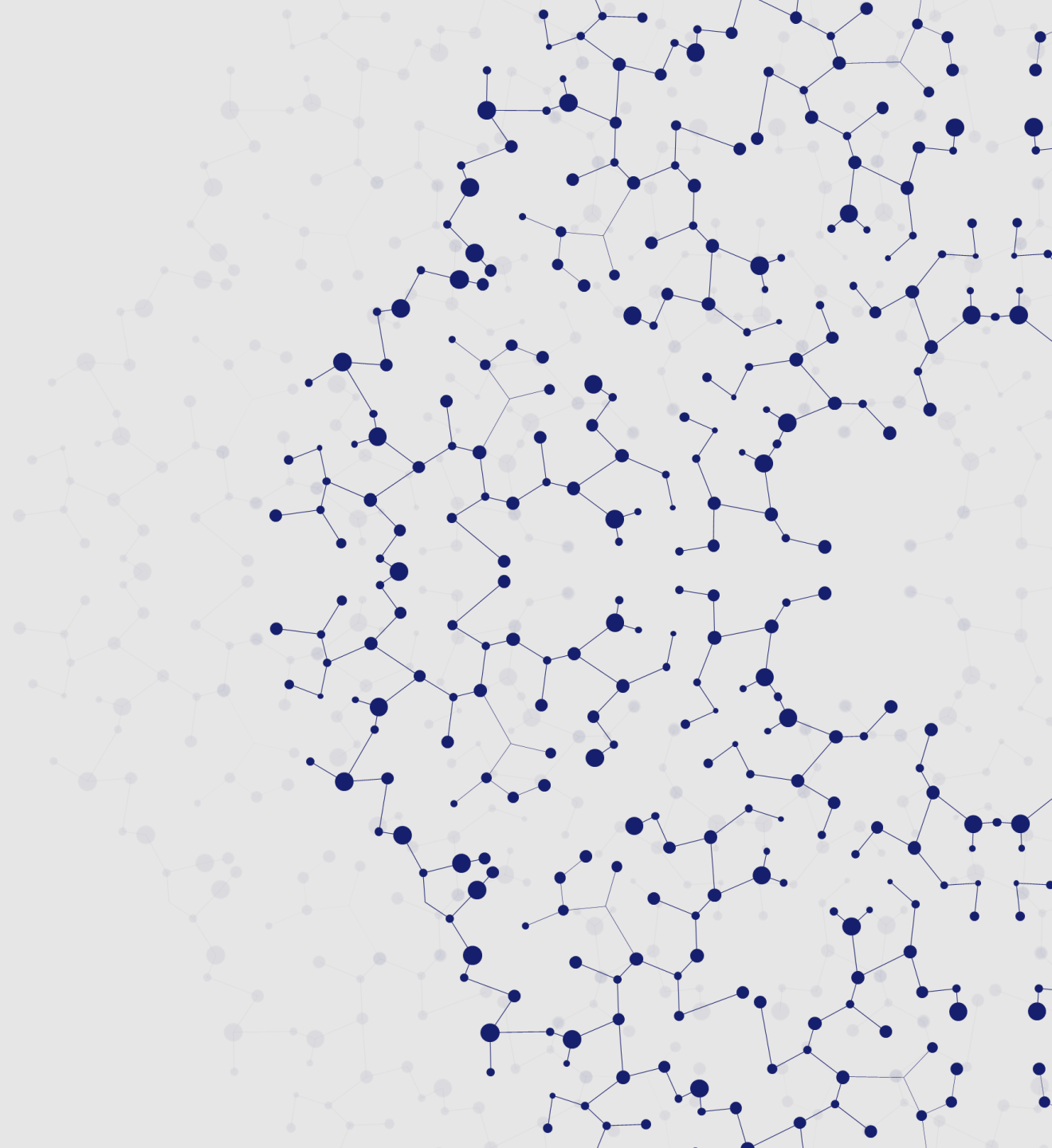
Glass Trace Elements - 670 kcps – 10 M counts



Reference composition determined by WDS

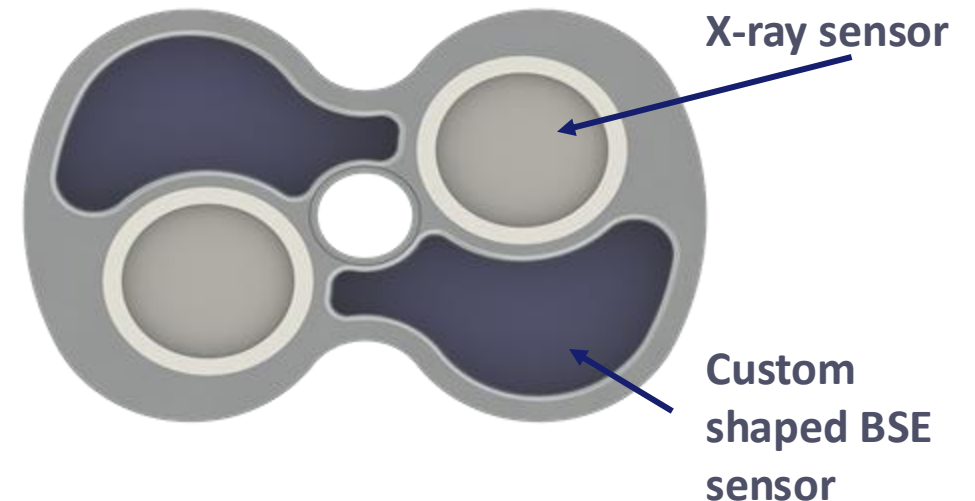
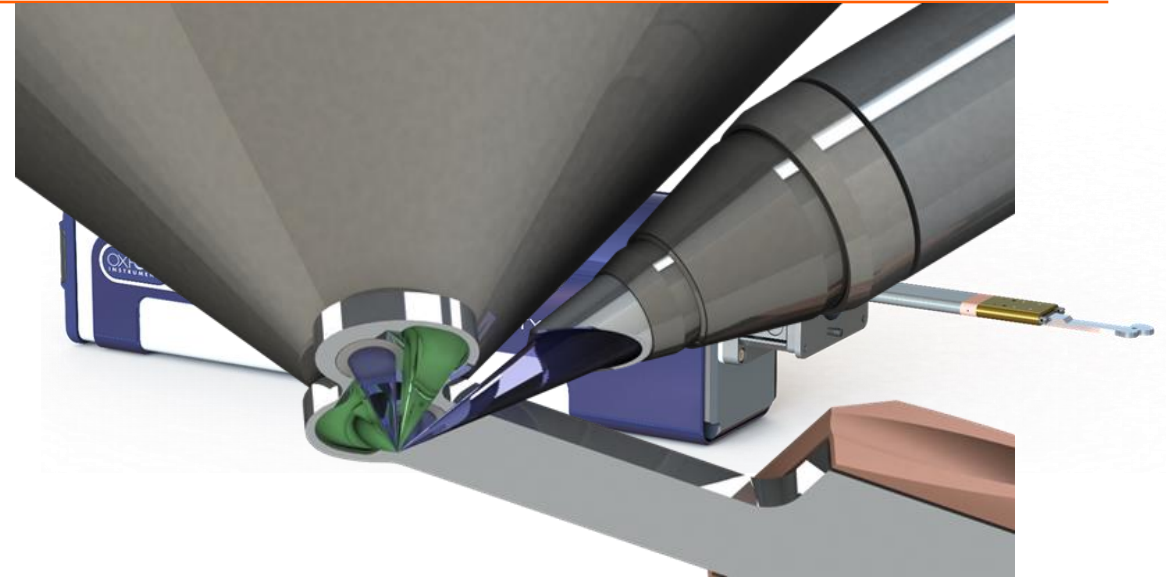
Error bars = 2σ

Minor and trace elements mapping with BEX



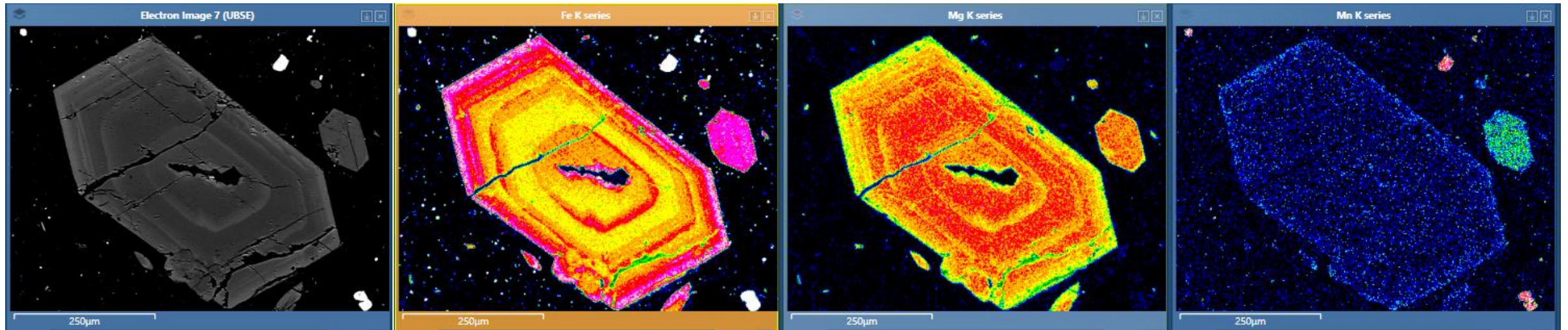
What is Unity?

- **Unity is the world's first BEX detector**
- **Retractable below the pole piece BEX detector**
- **Unity sensors**
 - **Two X-ray sensors (SDD)** providing enhanced sensitivity ranging from 7 to 120 times higher than typical EDS detectors (e.g. 20 X more sensitive than EDS 65mm² detector)
 - **Two custom shaped solid state BSE sensors** high end BSE sensors
- **Optimised to collect maximum signal without obscuring EDS**
- **Optimized head thickness (3mm) and central hole (3mm) for daily use**
- **Unity Head is Peltier cooled for optimum X-ray performance**
- **Unity design and AZtecLive software features reduces the risk of collision. In addition, the Unity head is replaceable for extra piece of mind**



Visualising minor and trace elements with BEX

Unity BEX & Ultim Max Infinity



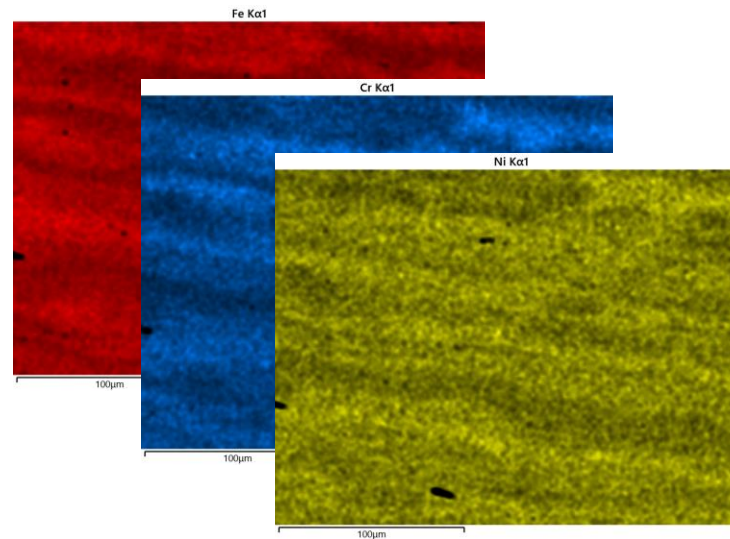
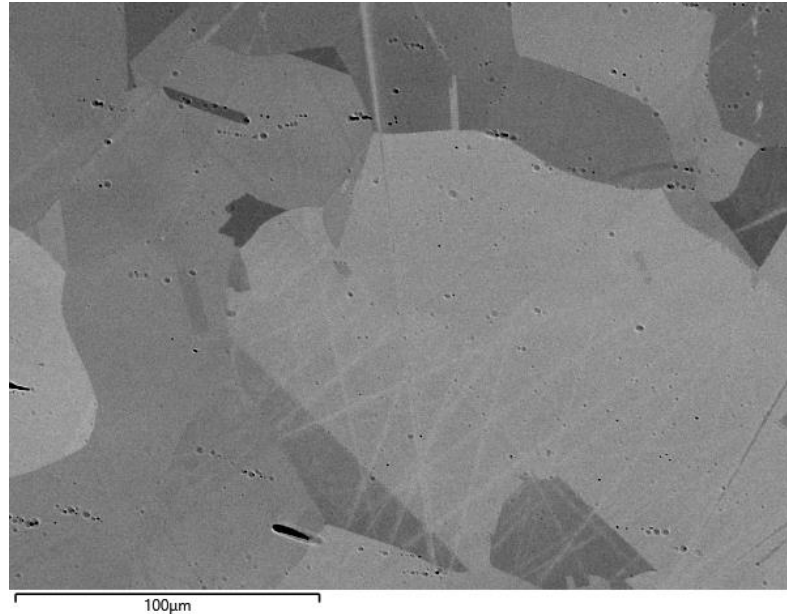
Mn rich rim <0.7 wt%

Challenge: Mapping elemental concentrations below 0.7 wt%

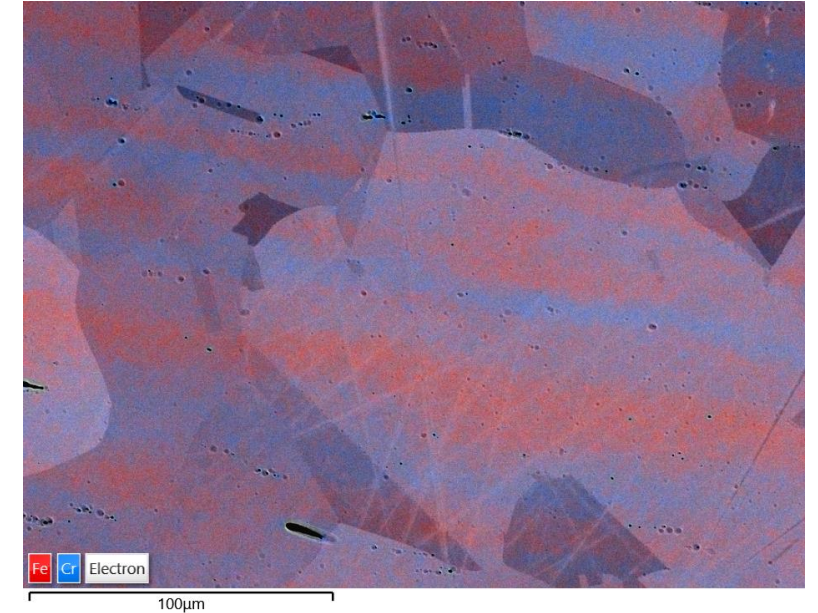
Unity captures incredibly high signal levels which allow us to visualise zonation of trace levels of Mn in this porphyritic dacite lava from Mt. Pinatubo, Philippines. Data was acquired in a single frame BEX acquisition (<20min) where equivalent WDS data would take at least 1 hour.

Visualising small element variation with BEX

Unity BEX, Ultim Infinity & AutoPhaseMap



Ni 0.1wt% delta Cr 0.4 wt% delta



Challenge: Mapping small element concentrations variation below 1 wt%

Unity captures incredibly high signal levels which allow us to detect segregation of Cr & Ni in steel in maps collected in just a few minutes. With Unity, we can use Cartography to extend this analysis to mm-scale samples, where WDS would require days to cover a similar area.

Most challenging EDS applications

Overlapped X-ray peaks of major elements

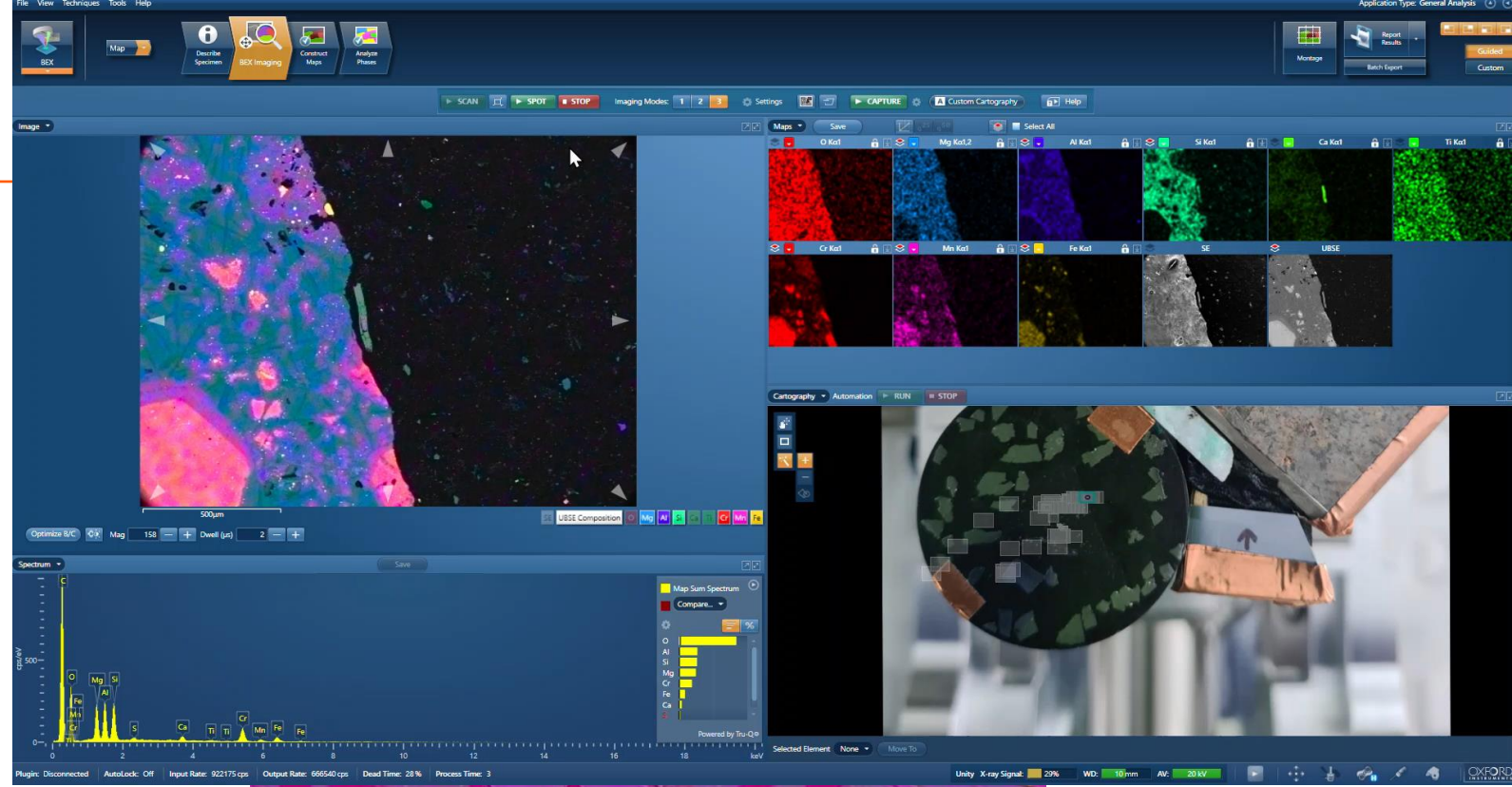
Trace elements with concentrations below 1 wt%

EDS quantification at high count rates (> 200 kcps)



Materials and methods

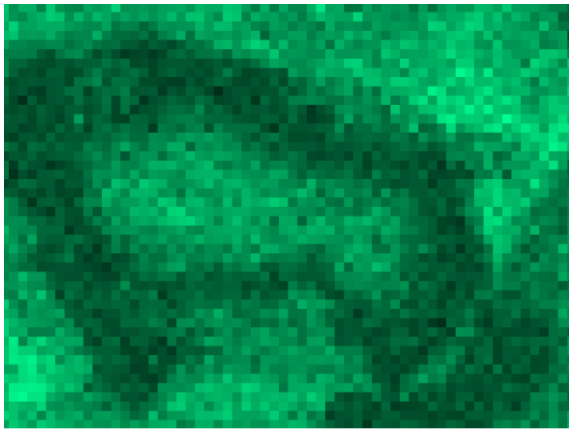
- **Challenge:**
- Well-defined standards containing minor and trace elements whose X-ray peak overlaps with other peaks
 - **Analysed samples: obtained from the experimental work in a steel production furnace** Mn (trace element) affected by overlap with Cr-K β (major element), 48 eV separation.
- **Standard steel sample (XPE alloy)** similar peak overlap between Cr-K β and Mn K α (17 wt% Cr, 0.05 wt% Mn)
- **Experimental setup:** EDS (Ultim Max Infinity 65, Oxford Instruments) WDS (AZtec Wave, Oxford Instruments,) Hitachi SU-70SEM



Heterogeneous microstructure contains various major elements and trace elements

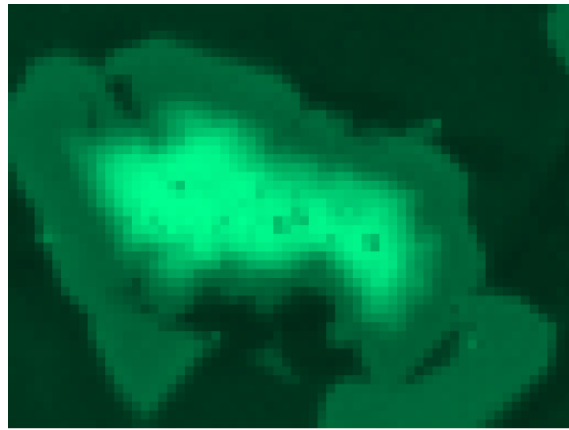
Analysis of unknown slag sample

- Mapping EDS and WDS, 20kV, 20nA using PT3 and an input count rate of 500 kcps (dead time of ~45%)
- WDS map reference, does not suffer from the strong overlap, and sum peaks



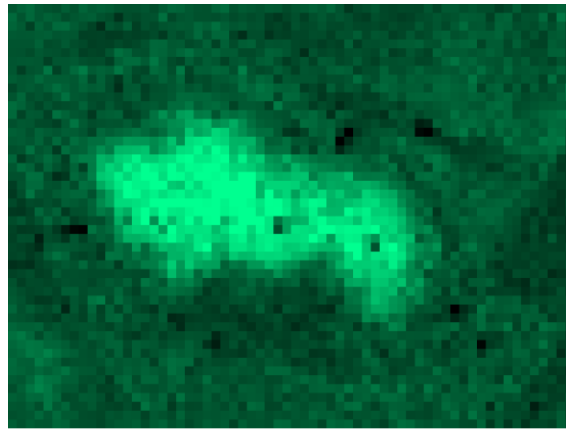
25µm

WDS



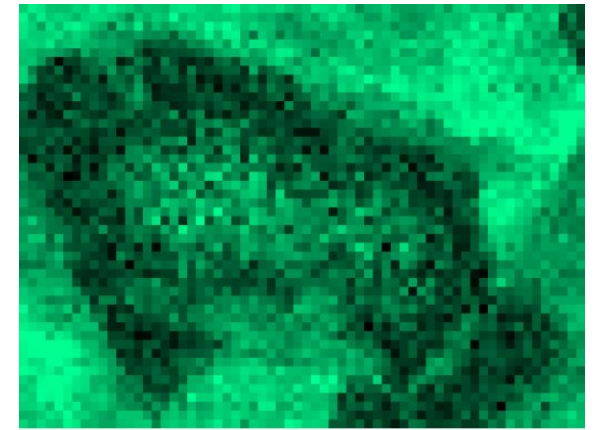
25µm

Window integral



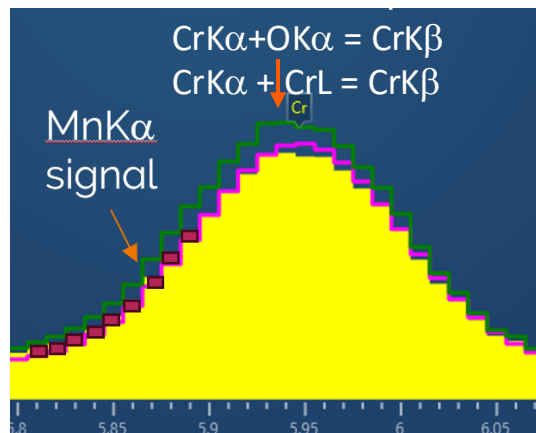
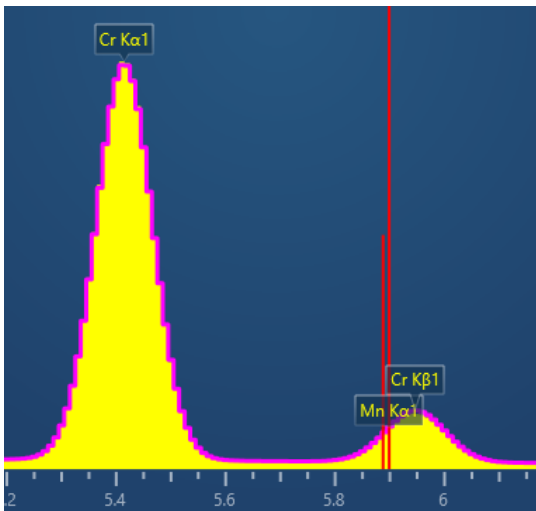
25µm

Peak deconvolution



25µm

Pulse pile-up correction and peak deconvolution



- Even after performing spectrum processing at every pixel of the map to filter the continuum and deconvolve peaks WDS and EDS maps do not display the same information.
- EDS true distribution after pulse pile up correction at every pixel-Mn 0.2 wt%

Summary: EDS has largely removed the advantage of SEM-WDS

30 Years of EDS Technology Development:

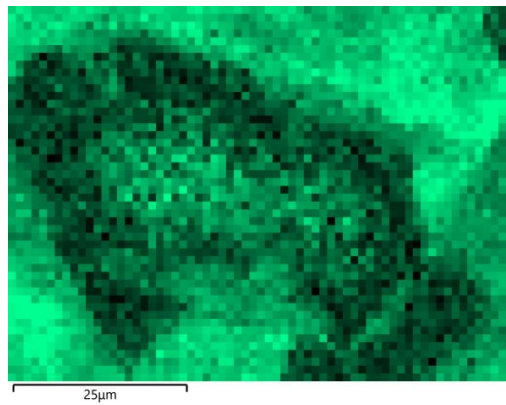
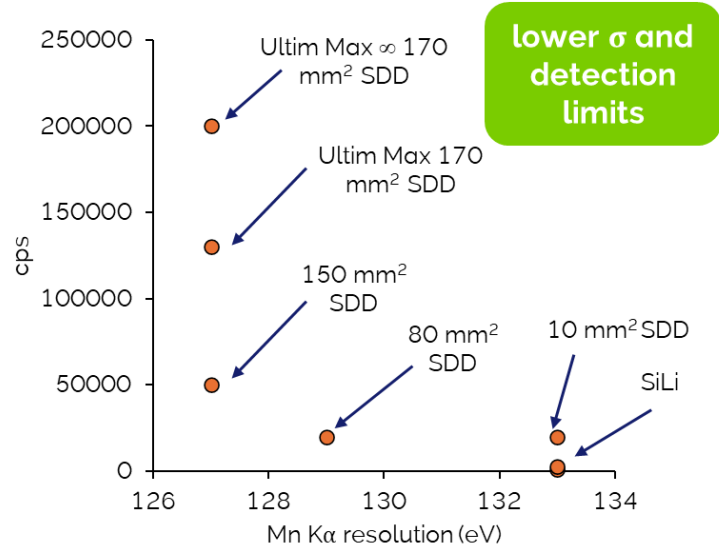
1. Digital Spectrum Processing
2. SDD and Large Area SDD
3. Spectrum Processing, Tru-Q and Tru-Q IQ
4. Low noise electronics
5. Pulse pile up correction

EDS technology can now rival WDS data quality for the most complex tasks...

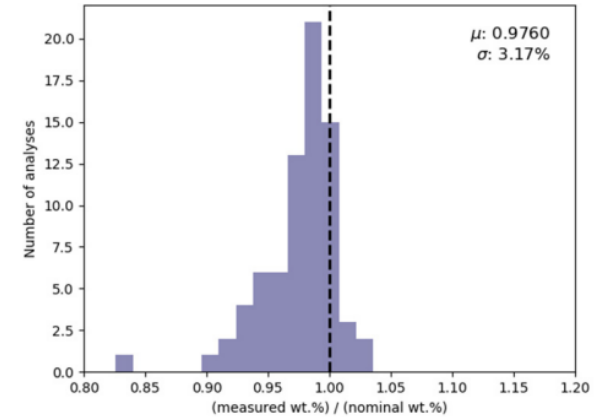
1. Peak overlaps
2. Quantification: major, minor AND traces
3. Mapping: minor and trace elements

User friendly, simultaneous acquisition, much faster

Generate lots of counts in far less time!!



20 kV, 200 kcps



Detection Limit in Steel – 20 kV – 100 M counts

Element	Wt. %	Wt. % σ	Detection limit (3 X wt.% σ)
Ti	1	0.004	0.012

Bulk (wt.%), Ni = 8, Fe = 70, Mn = 2, Cr = 19, Ti = 1

WDS like data quality

Thank you for your attention!

Dr. Lucia Spasevski
Product Manager
Lucia.Spasevski@oxinst.com



Time for your questions